



<https://www.desy.de/>

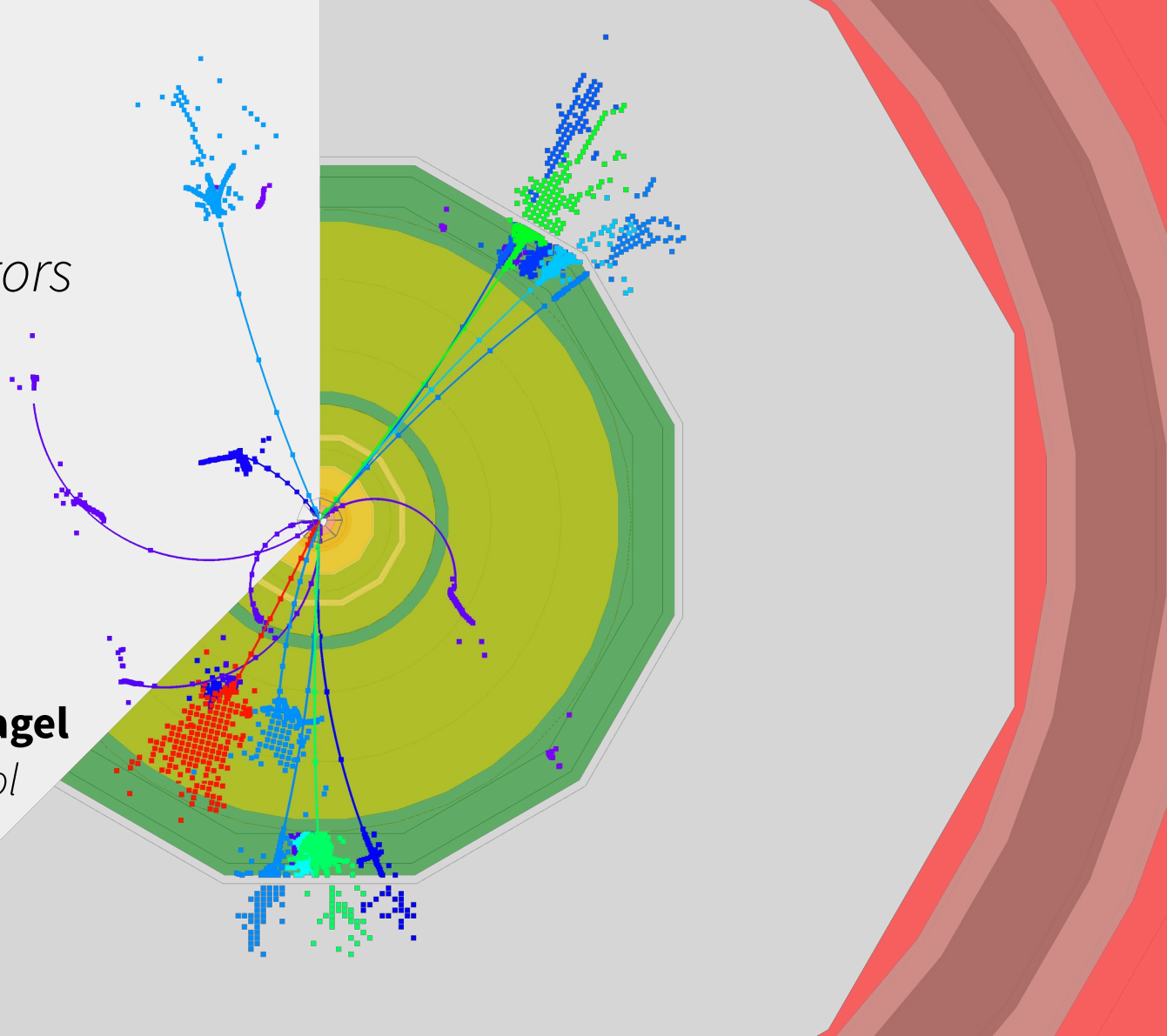
Silicon Detectors III

Sensors for Hybrid Detectors

Simon Spannagel

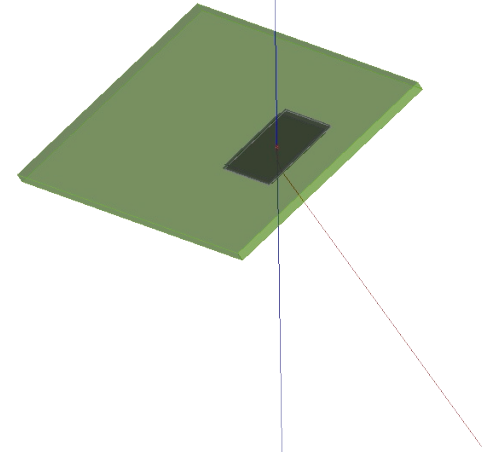
EURIZON Detector School

19 July 2023

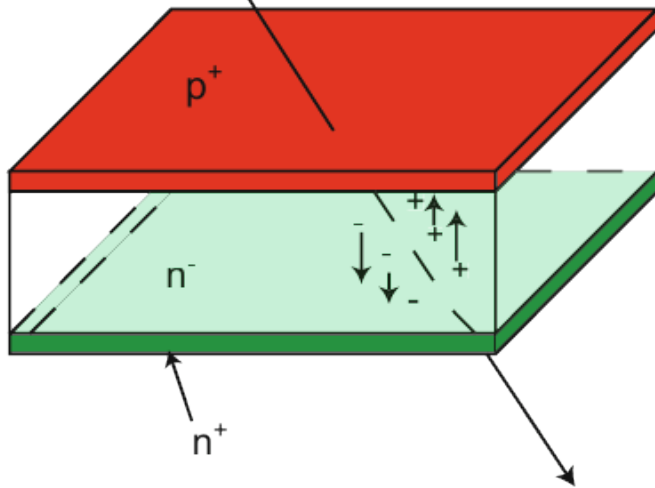


Recap:

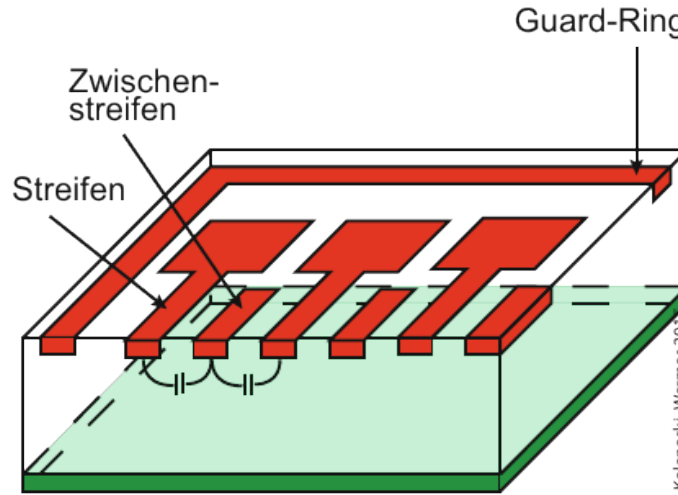
Segmented Silicon Detectors



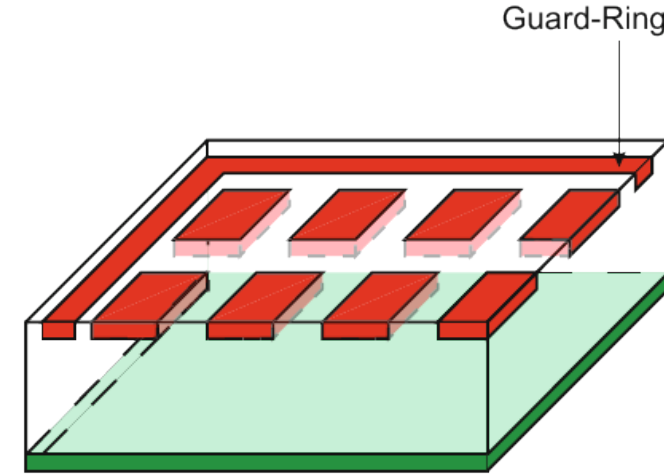
Diode, Strip & Pixel



- Simplest geometry
- No position measurement



- N channels
- Straight-forward connection to ASIC
- Problem of ghost hits

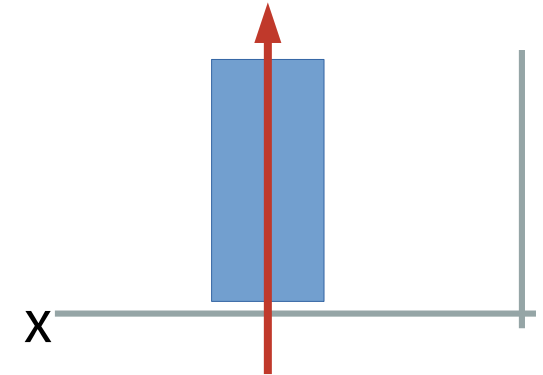


- N^2 channels
- Intrinsic 2D measurement
- Issue connecting channels

Spatial Resolution – Summary

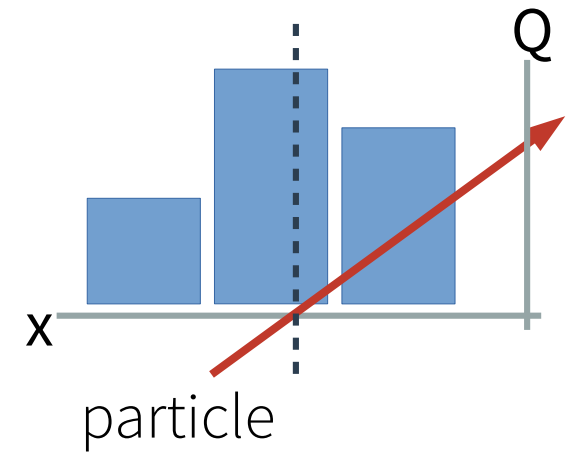
- Just a **single channel** struck:
precision limited to variance of uniform distribution

$$x = x_i \quad \rightarrow \quad \sigma_x = d/\sqrt{12}$$



- **Multiple channels** struck (charge sharing):
interpolation using relative energy / charge distribution

$$x = \frac{\sum_{i=1}^N q_i x_i}{\sum_{i=1}^N q_i}$$



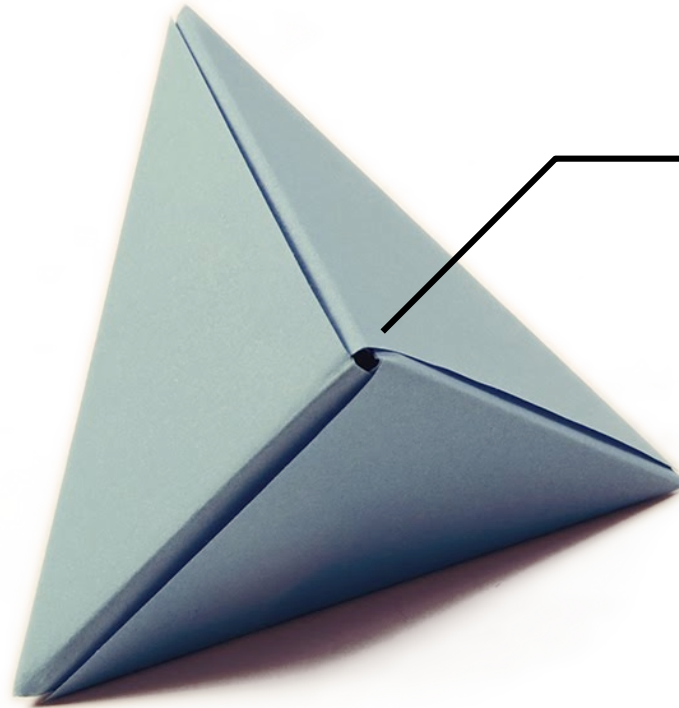
Challenges for Silicon Detectors

Material Budget

Radiation Hardness

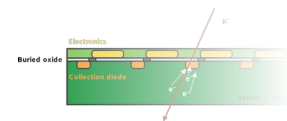
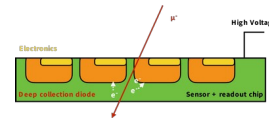
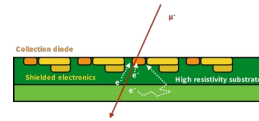
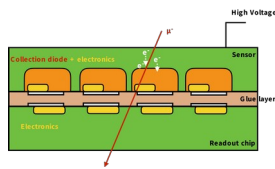
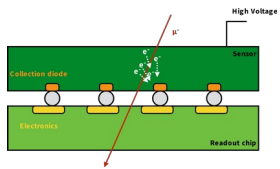
Resolution &
Granularity

Readout Speed &
Power Consumption

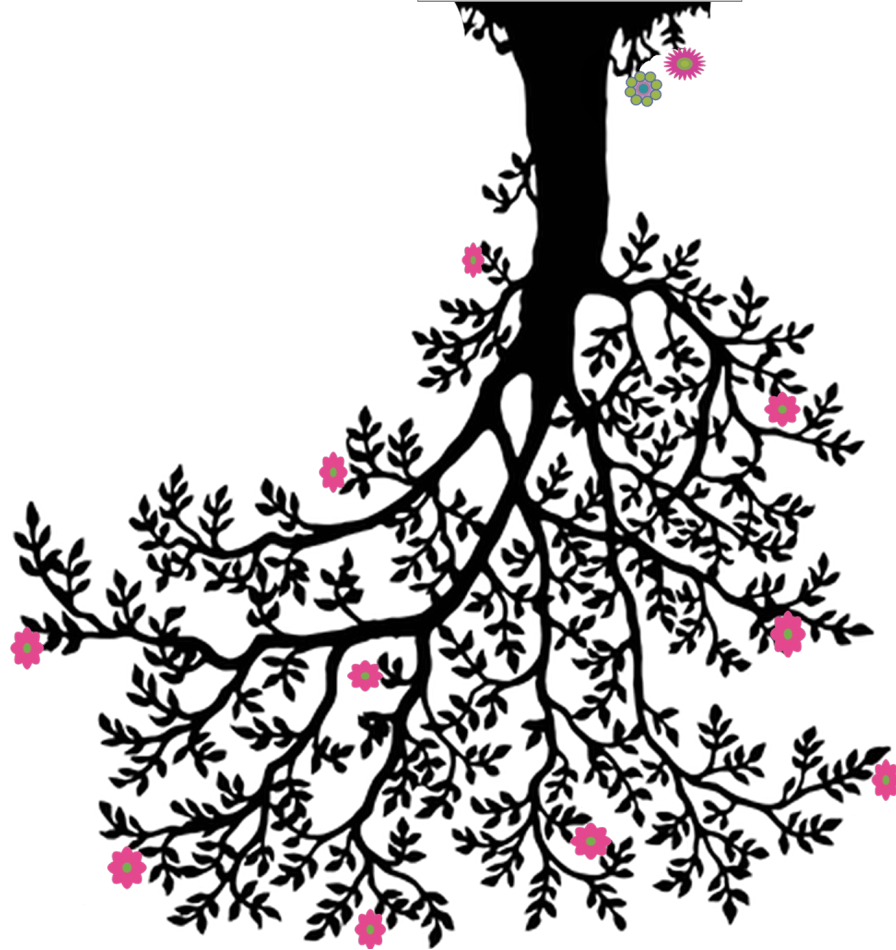


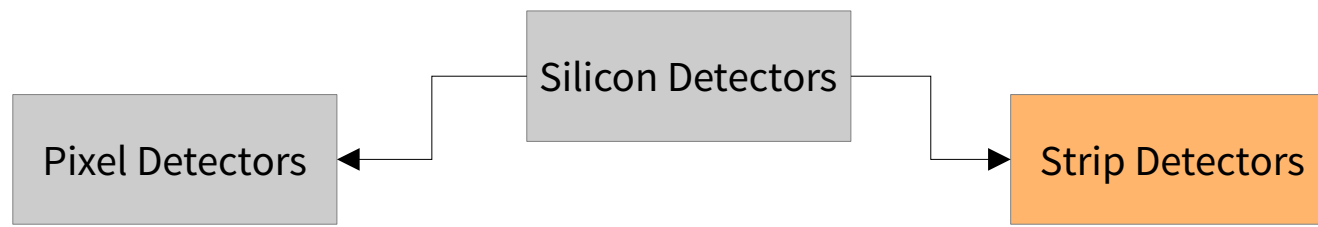
(Some) Silicon Sensor Technologies

for Vertex & Tracking Detectors



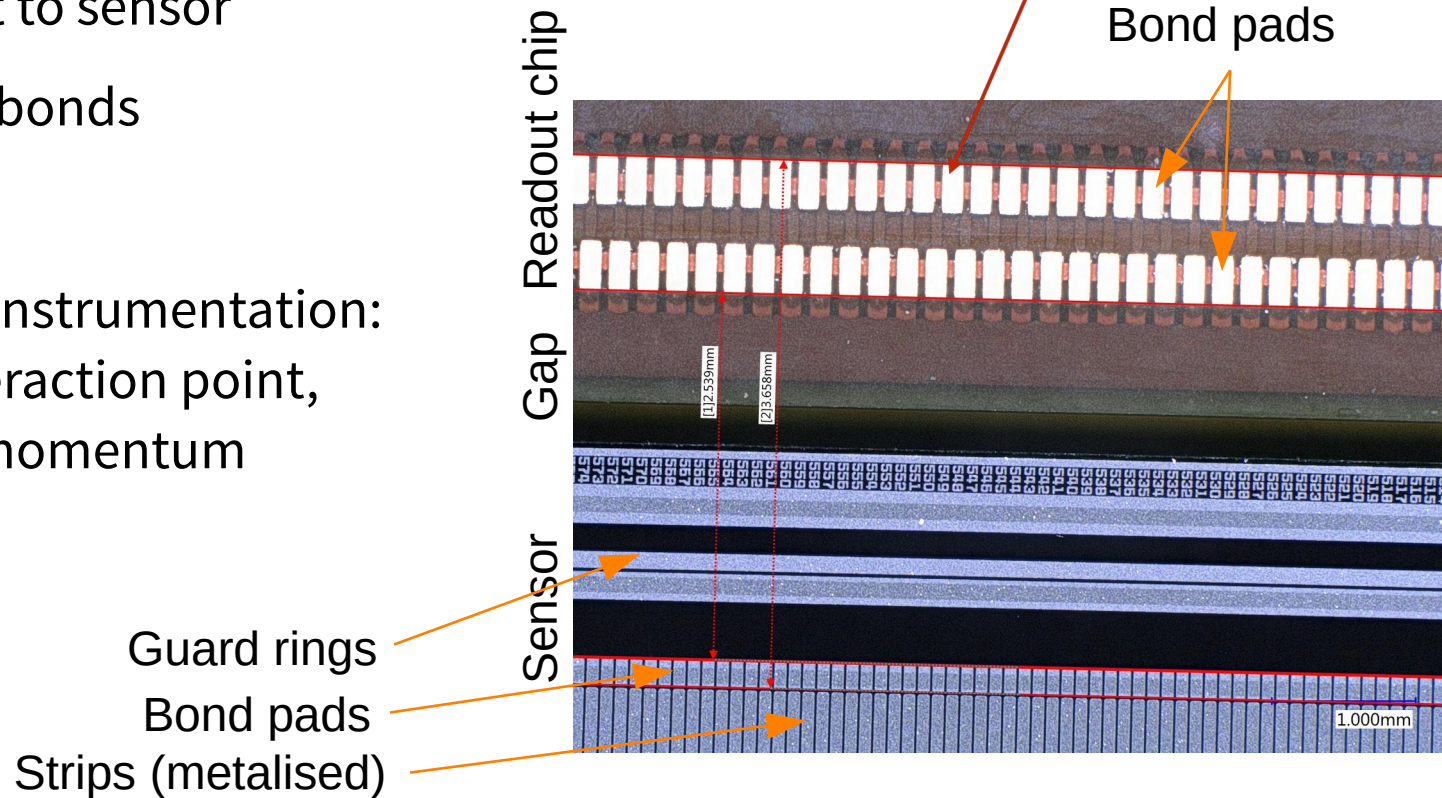
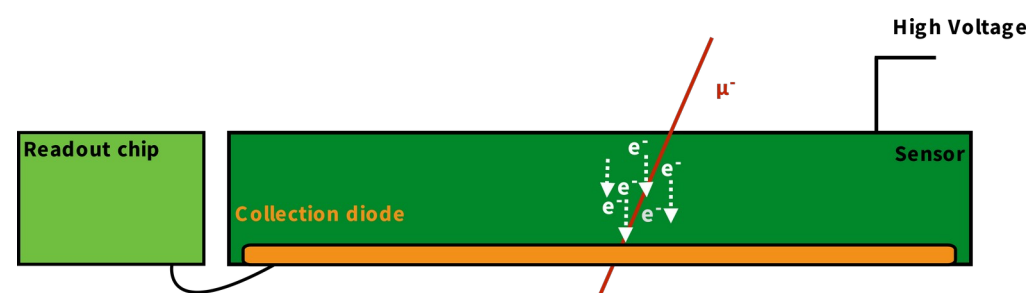
Silicon Detectors





Silicon Strip Detectors

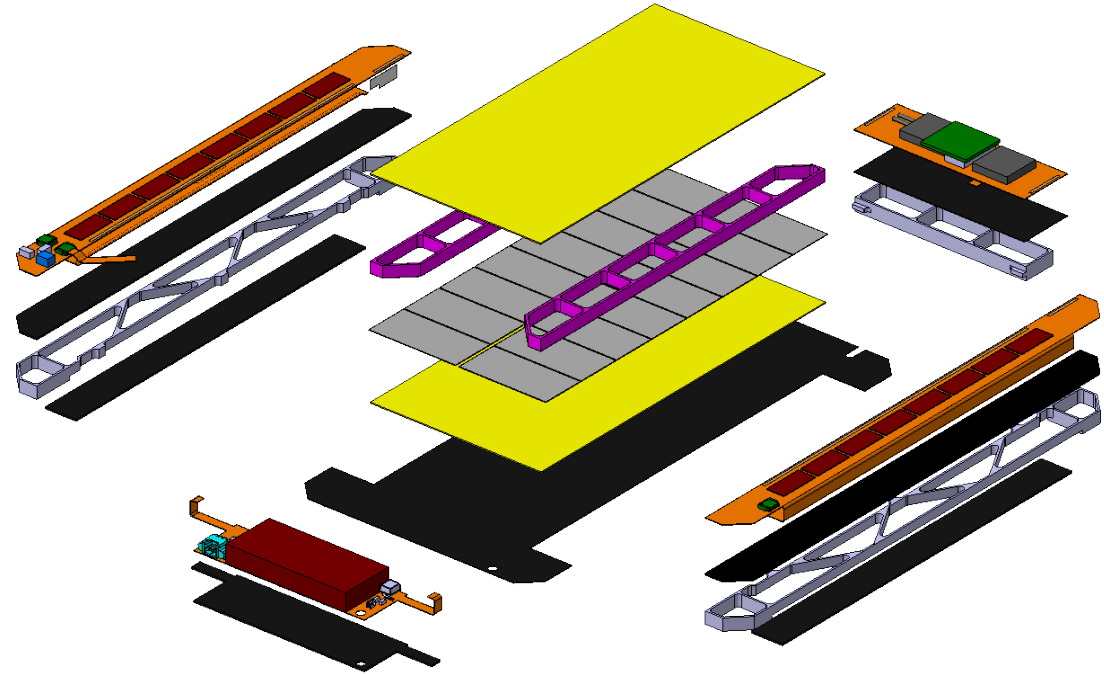
- 1D segmentation of electrodes
- Electronics adjacent to sensor
- Connection via wirebonds
- Used for large-area instrumentation:
Large radii from interaction point,
large lever arm for momentum
measurements



Detector Modules – Complex Structures

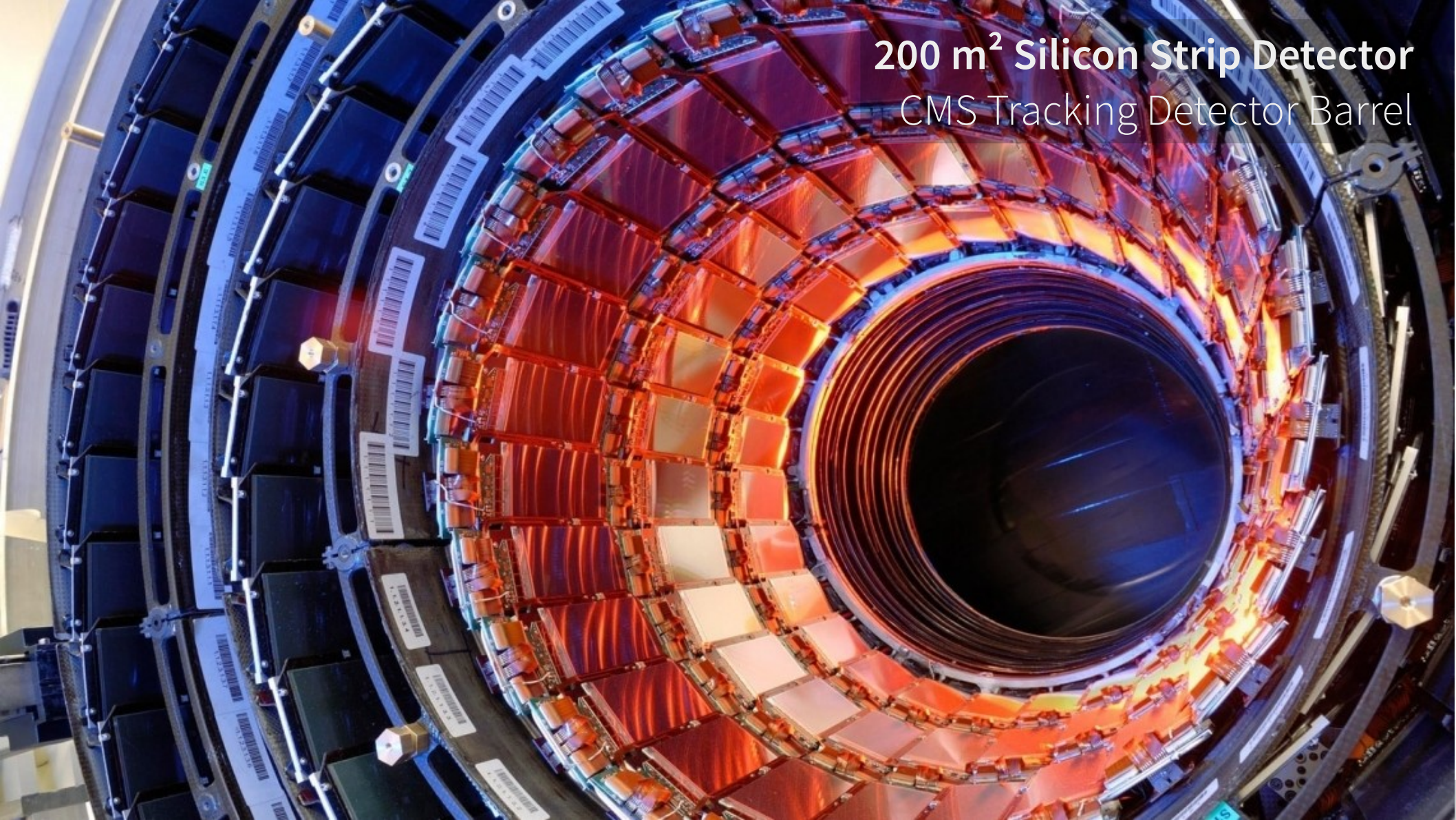
- Sensor is only one part of complex system, that contains...
 - Readout ASICs
 - DC-DC converters
 - Optical transmitters
 - Electrical interconnects / flexprints
 - Mechanical support, spacers
 - Thermal contacts
 - ...

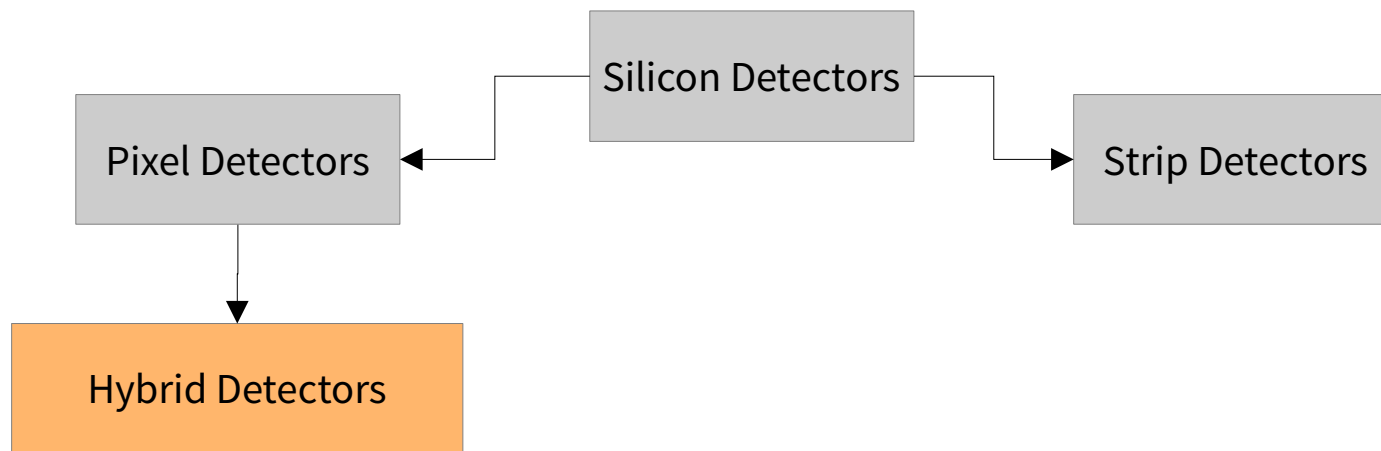
CMS Phase 2 Tracker Upgrade
PS Module exploded view



- Very complex to assemble at micrometer precision level!

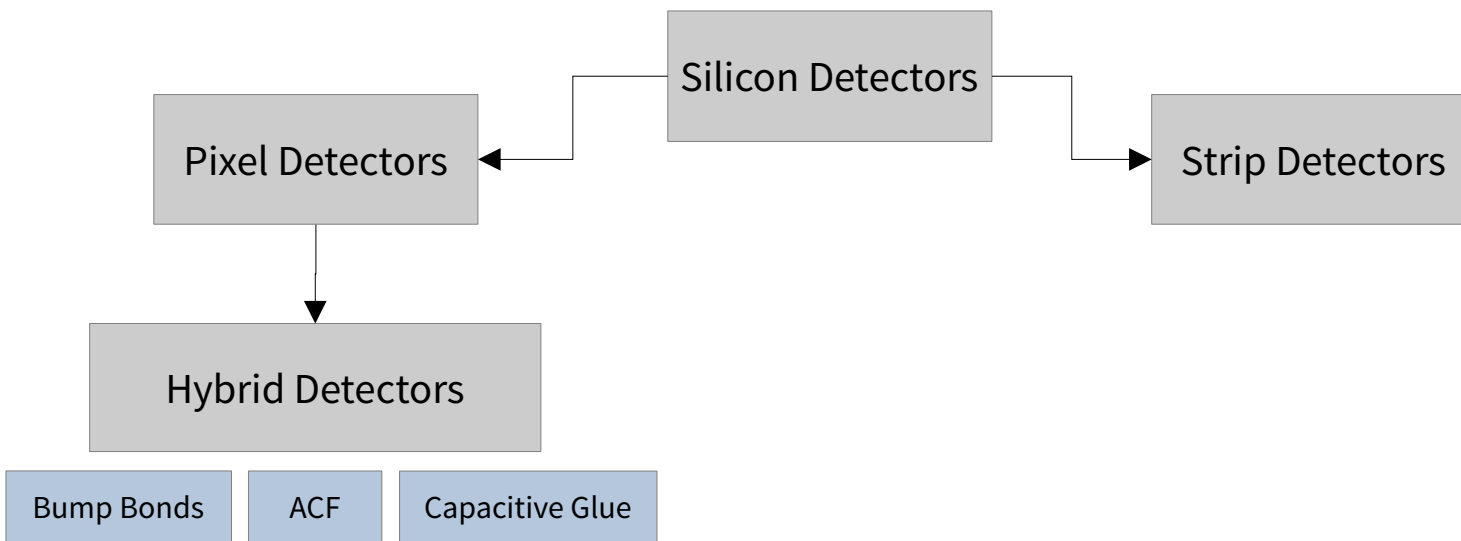
200 m² Silicon Strip Detector
CMS Tracking Detector Barrel





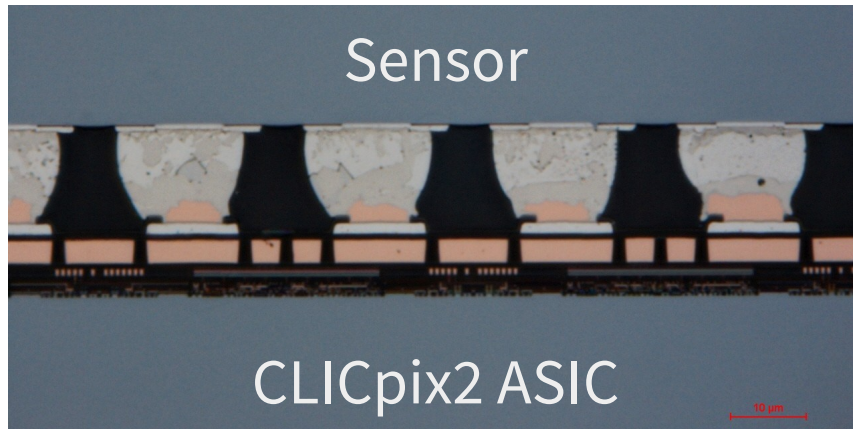


Hybrid Silicon Pixel Detector
100 μm Timepix on 100 μm Sensor

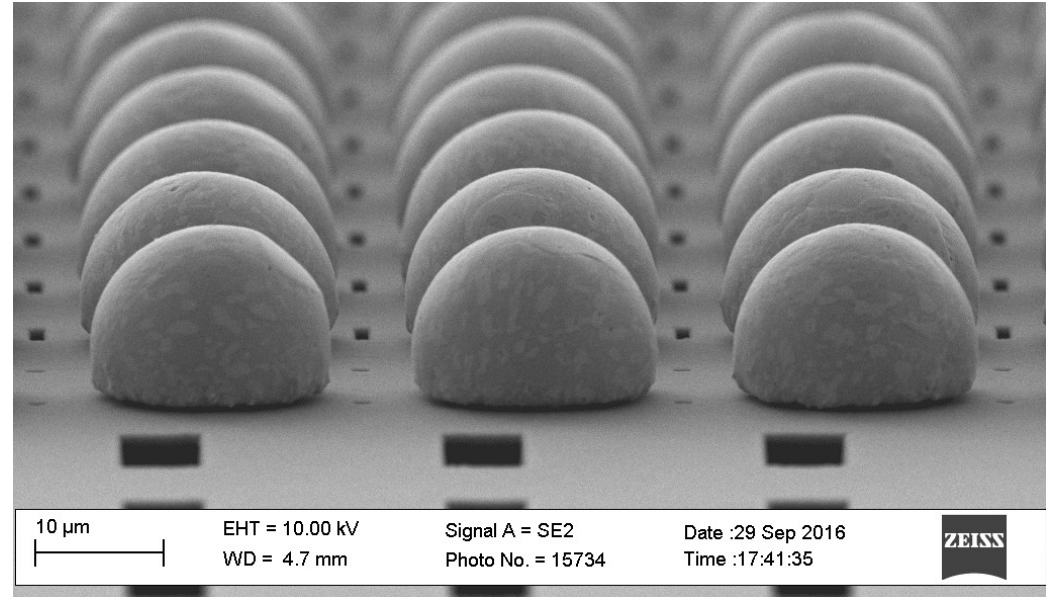


Hybridization: Bump Bond Interconnects

- Different technologies available
- Very common: Bump bonding
 - Size: $\sim 20 \mu\text{m}$
 - Material: Lead-Tin, Indium, ...



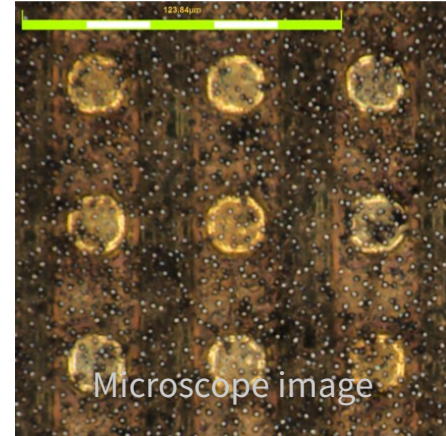
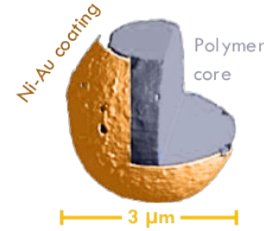
<https://doi.org/10.1088/1748-0221/14/06/C06003>



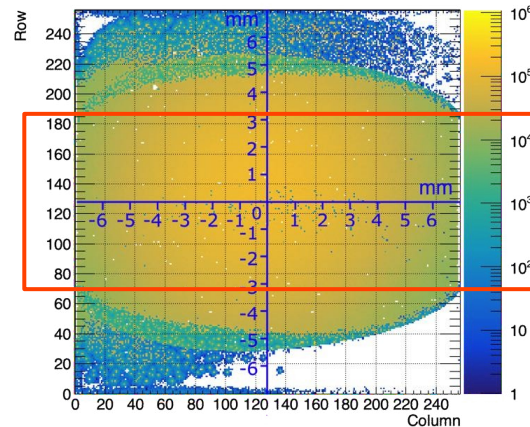
- Different placement techniques
 - Solder spheres \rightarrow individual chips
 - Via lithography \rightarrow wafer-level

Hybridization: Anisotropic Conductive Film

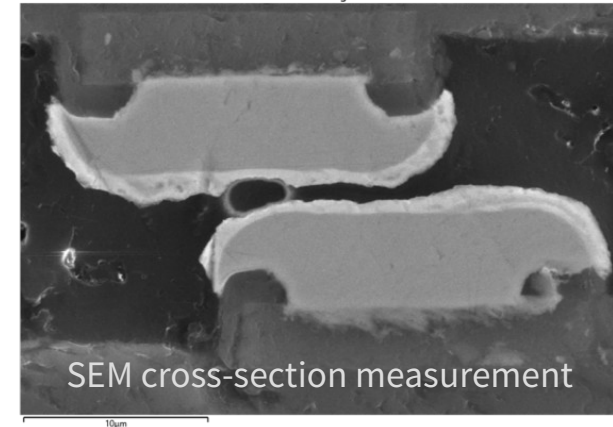
- Alternative to traditional solder-bump bonding
- Adhesive film with conductive micro-particles
 - Stochastically distributed in film
 - Some spheres end up under bond pads, get deformed, establish contact
- Widely used in display industry in one dimension, challenge: 2D distribution



- Requires careful optimization of
 - Film thickness
 - # spheres/area
 - Bonding force...
- Currently in R&D phase

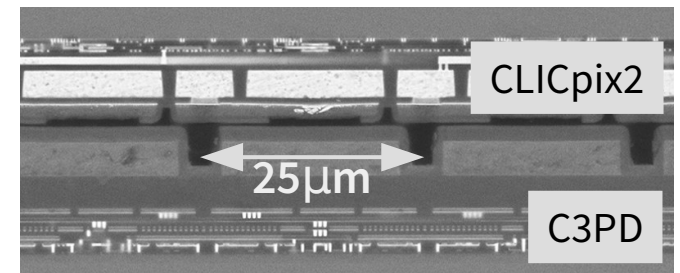
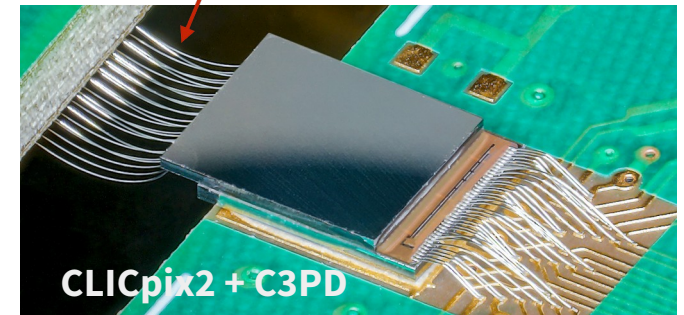
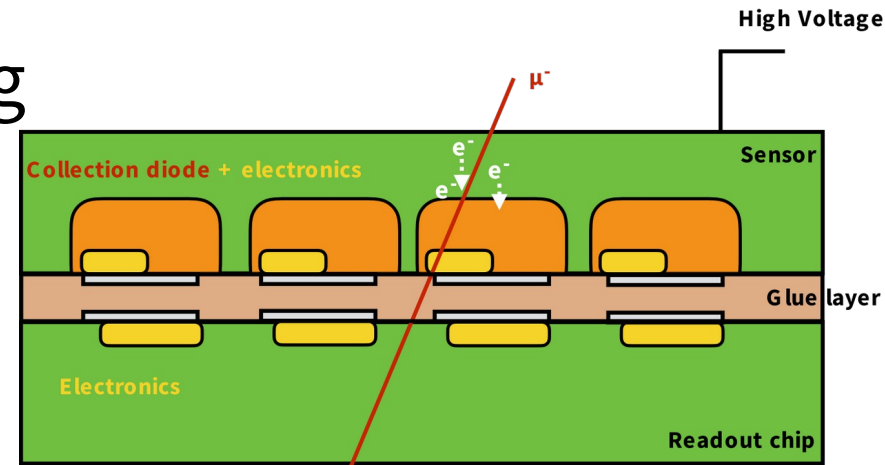


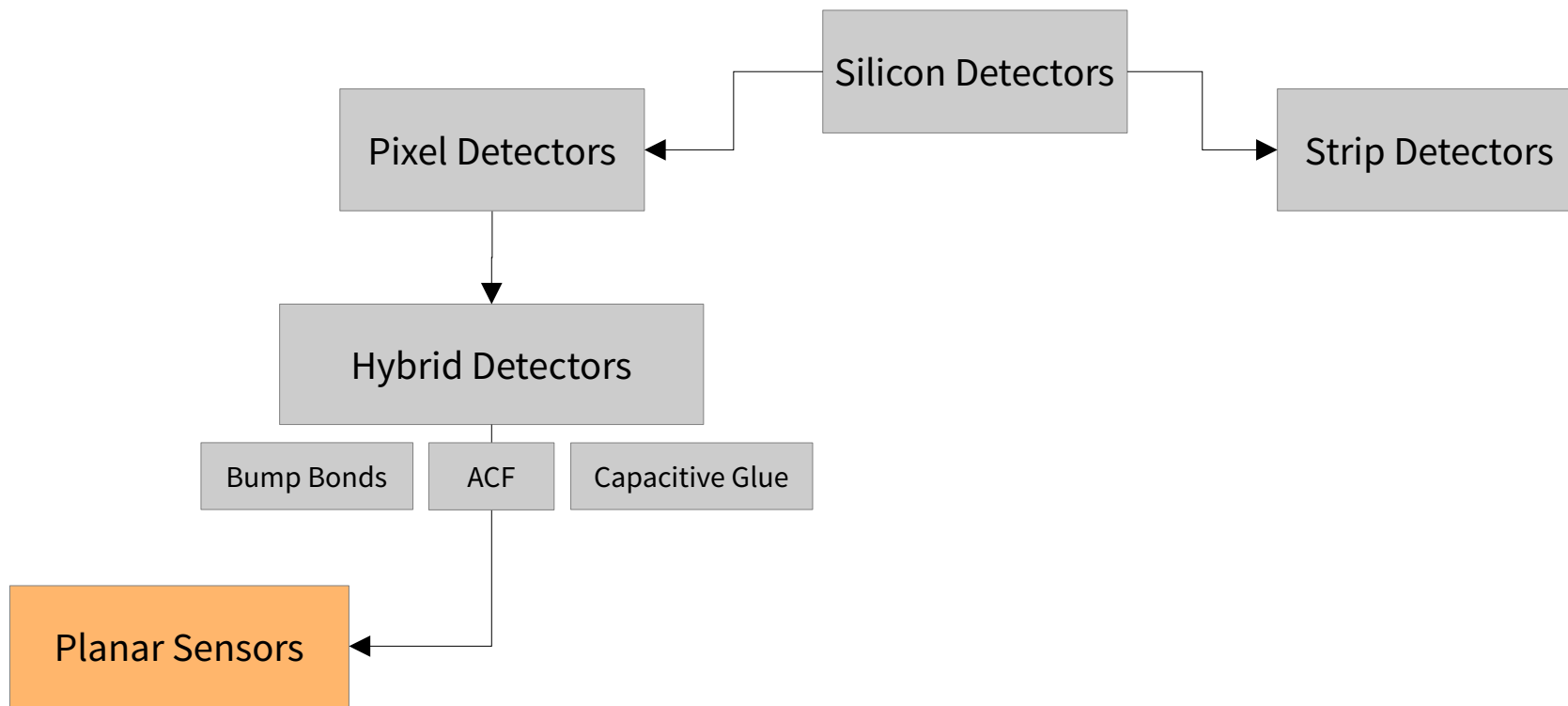
← ~20μm →
Electron Image 6



Hybridization: Capacitive Coupling

- Combination of “traditional” readout chip and active sensor
- Only analog part (amplification) in sensor
- Advantages:
 - Large signal from amplifier while rather simple circuitry in sensor
 - Can use full feature set of readout chip CMOS process
- Challenges:
 - Gluing requires precise alignment
 - Main influence: distance – good uniformity required
 - Requires connecting & powering two chips





Planar Silicon Sensors

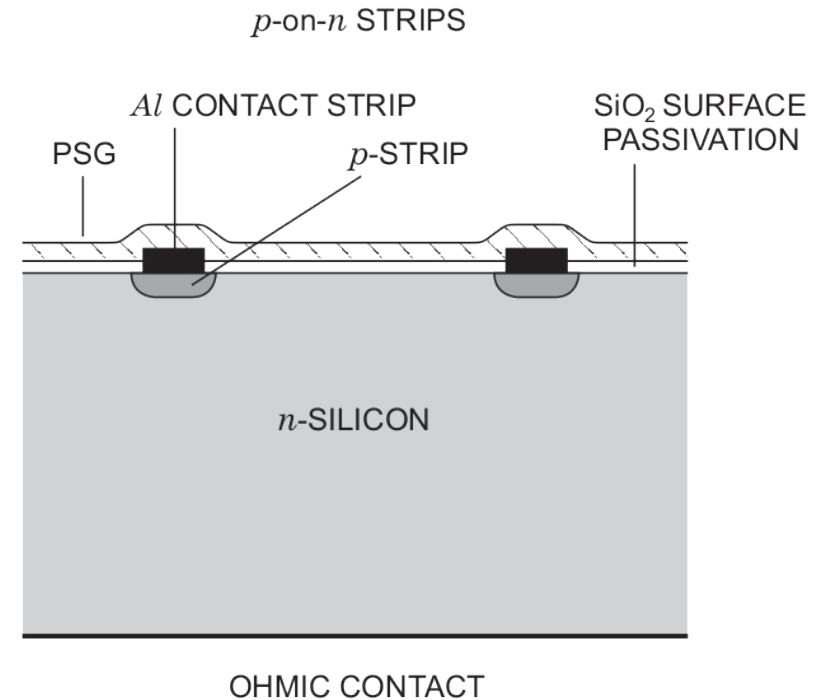


typical doping (*p-in-n* sensor):

$$N_A \approx 10^{15} \text{ cm}^{-3}$$

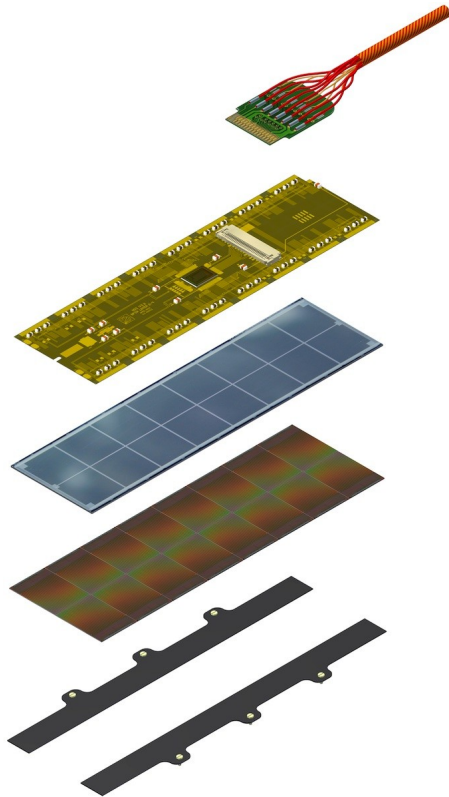
$$N_D \approx 10^{12} \text{ cm}^{-3}$$

- Asymmetric pn-junctions, here: *p-in-n*
 - Lightly doped *n* bulk sensor material
 - Thin, highly-doped *p* implant
 - Segmentation of implant: separate channels
 - Backside: layer of highly doped *n*⁺ as ohmic contact
-
- ✓ Straight-forward production,
Well-studied sensor designs
 - ✓ 100% “fill factor” / fully efficient
 - ✗ Long drift times lead to charge loss after irradiation



H. Spieler

Example: CMS Pixel Detector



Twisted pair cable

HDI (High Density Interconnect, signal and power handling)

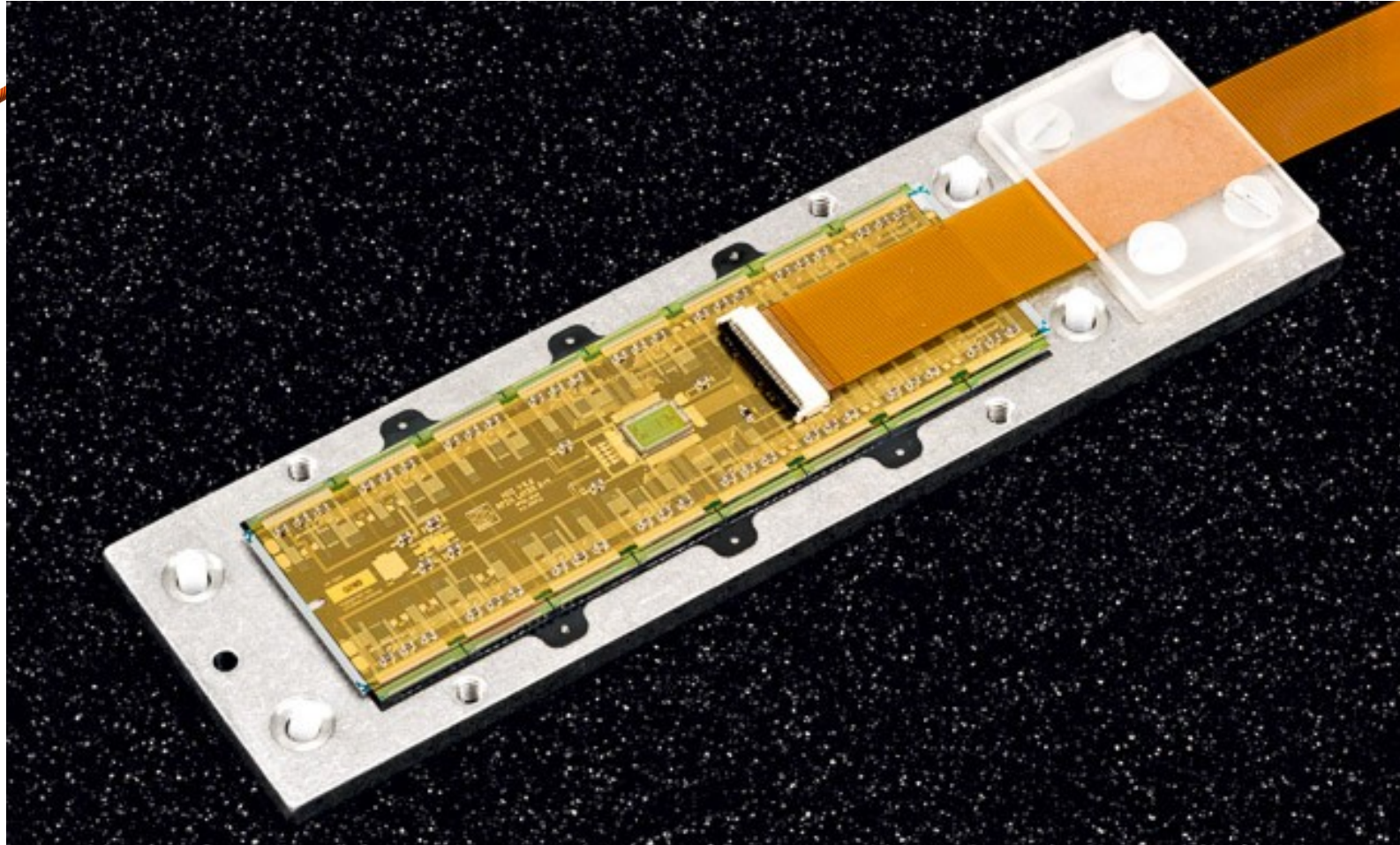
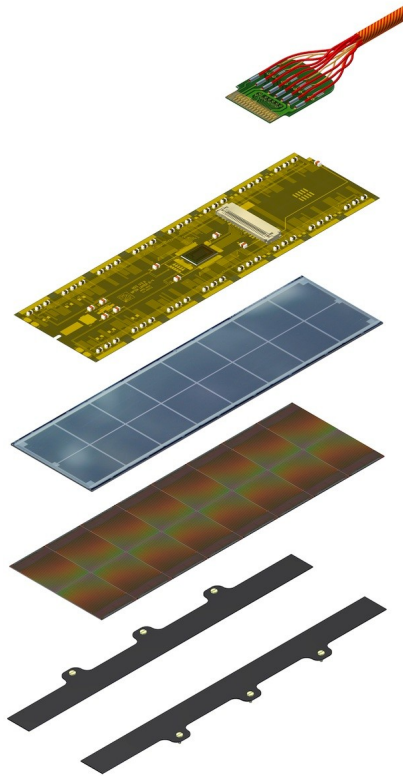
n⁺-in-n silicon sensor

16 readout chips, bump bonded to sensor

Base strips for mounting

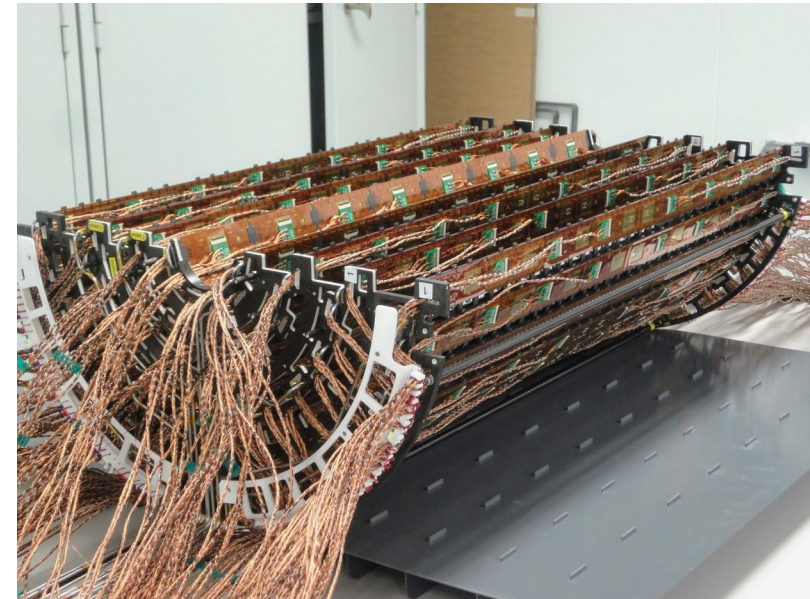
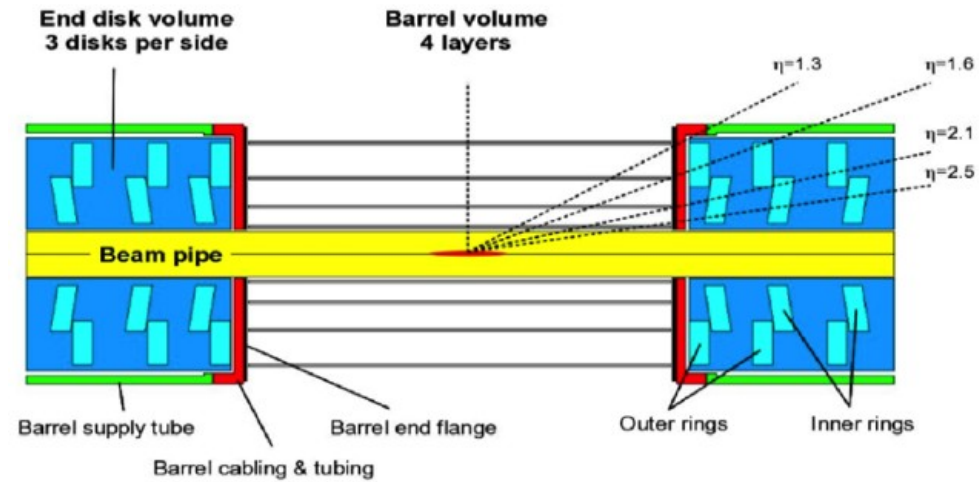
- Sensor:
 - n⁺-in-n sensor technology
 - 285 μm thickness
 - 150 x 100 μm pitch
- Module:
 - 52 x 80 = 4160 pixels/chip
 - 16 chips → 4160 x 16 = 66560 pixels/module
 - Total size: 64.8 x 16.2 mm

Example: CMS Pixel Detector



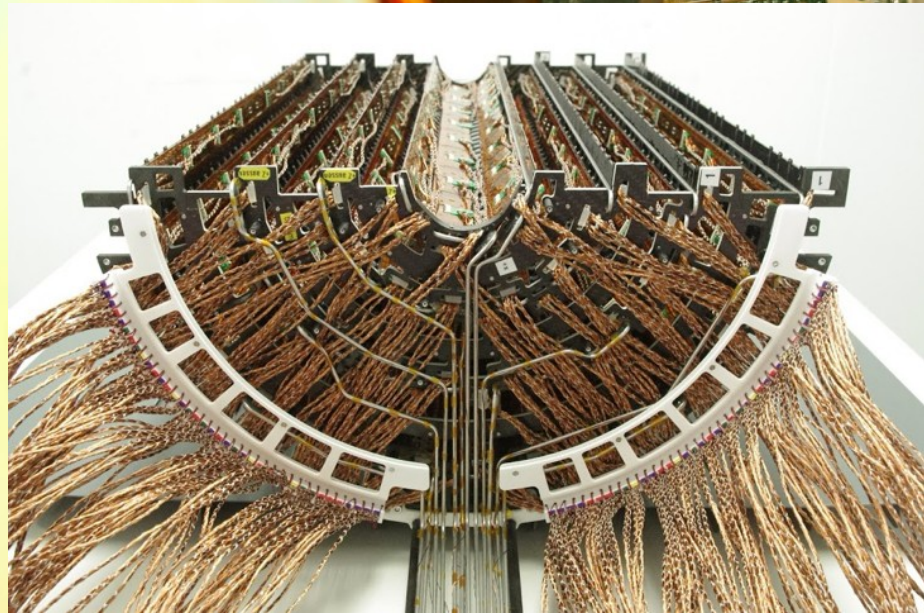
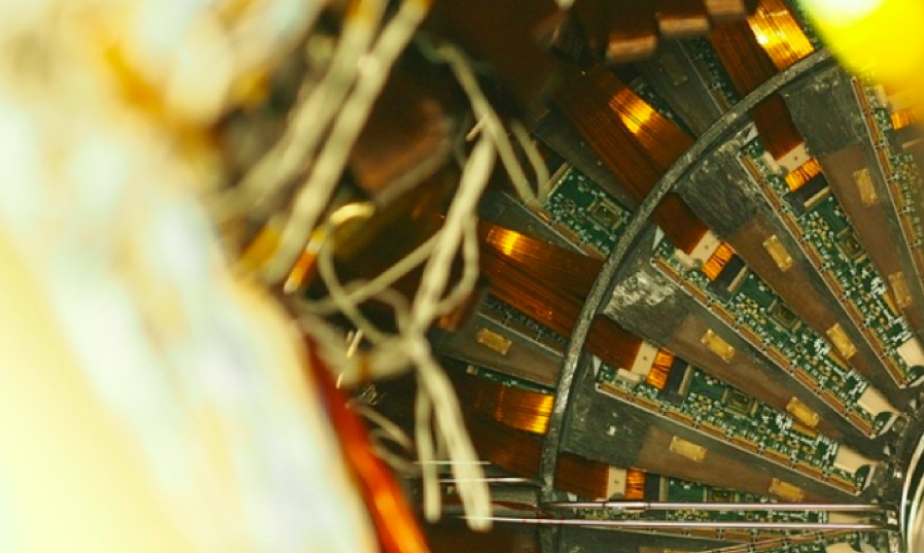
Example: CMS Pixel Detector

- Innermost part of the CMS Detector
 - Four *barrel* layers
 - Radii: 3.0, 6.8, 10.2, 16.0 cm
 - Length: 54.9 cm
 - Three *endcap* layers per side
 - Radii: 4.5 – 16.1 cm
- Total number of modules: **1856**
- *124 MPix* – with 25 ns time resolution
- Spatial resolution: $> 5 \mu\text{m}$

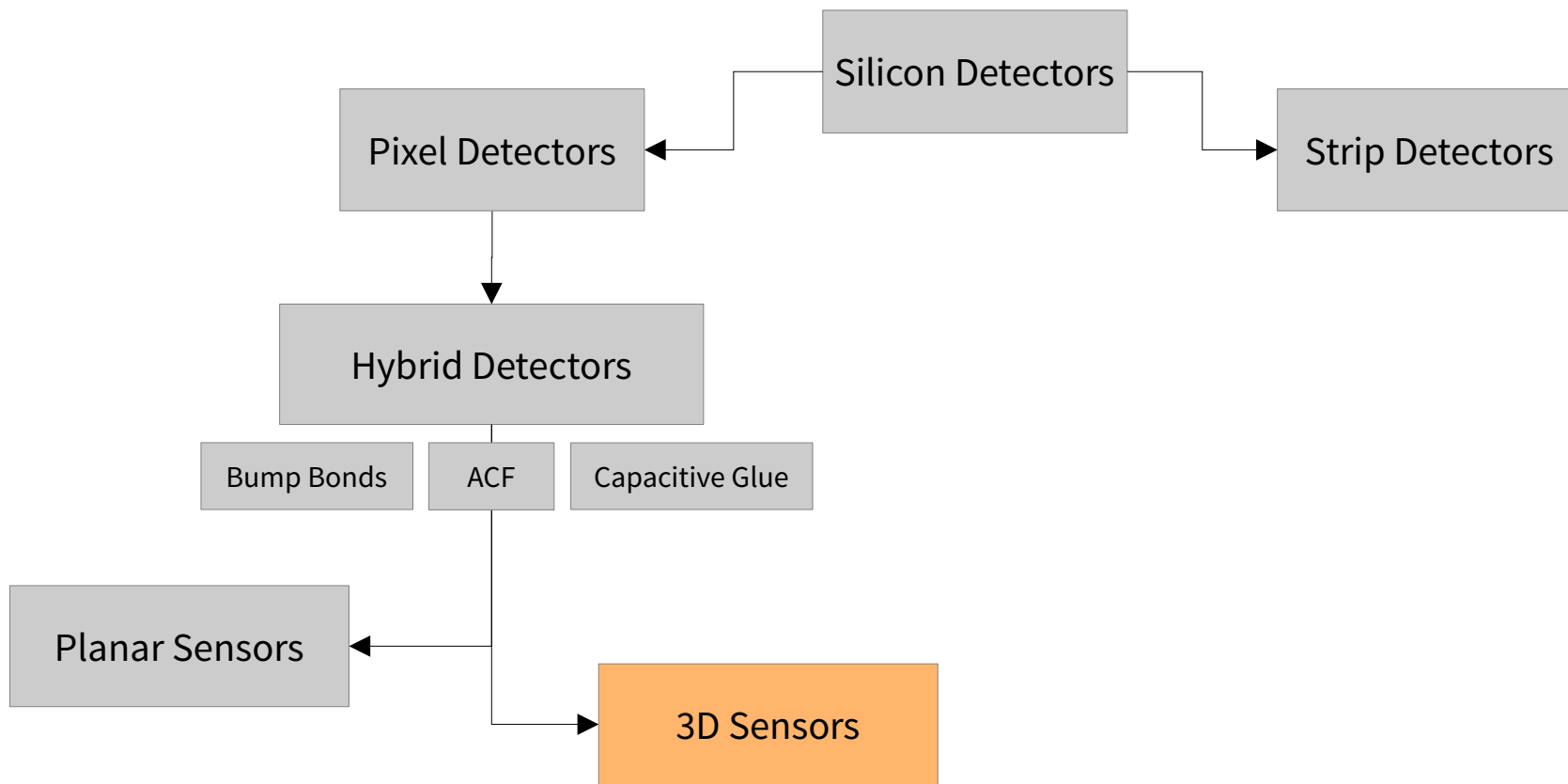




Installation of the Phase I Pixel Detector
CMS Experiment @ LHC

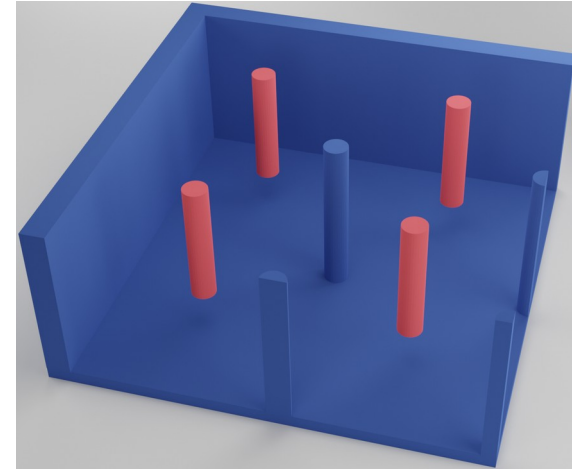


Endcap and Halfbarrel
CMS Phase I Pixel DeteCtor

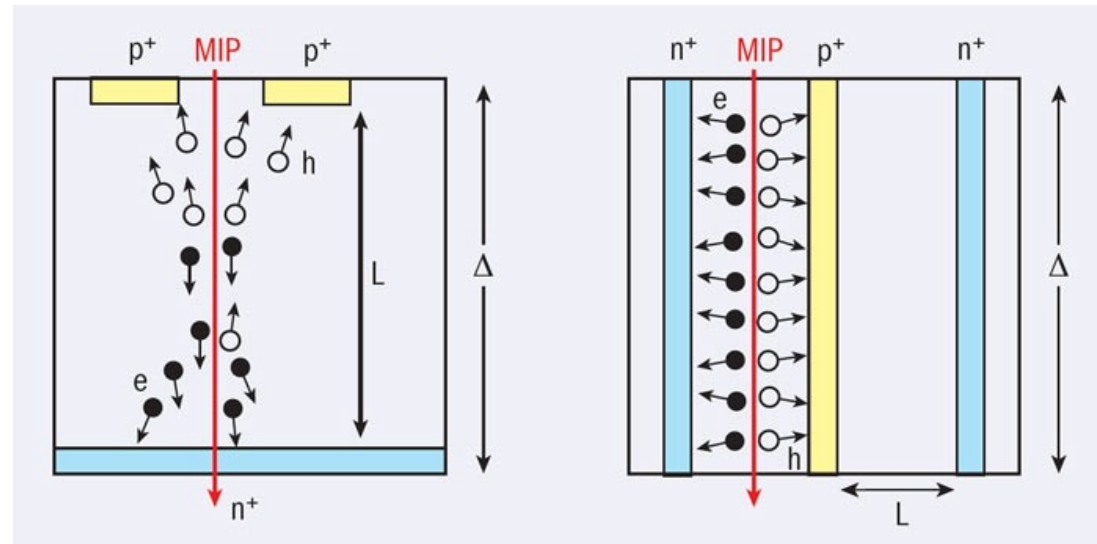


3D Silicon Sensors

- p- and n-implants implemented as columns
- Vertical implants: horizontal pn-junction
- Electric field forms horizontally between columns

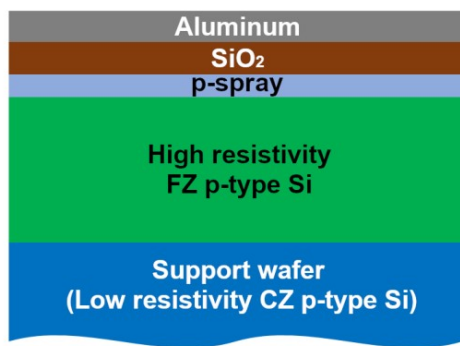


- ✓ Short drift time \rightarrow fast!
- ✓ High radiation tolerance
- ✗ High production costs & time
- ✗ Inefficiencies at vertical incidence



3D Silicon Sensors: Production

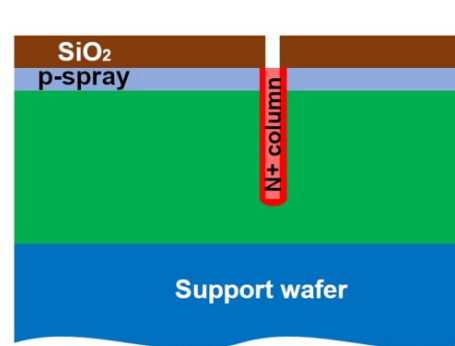
- DRIE (Deep Reactive Ion Etching): used in industry for MEMS, TSVs, ...



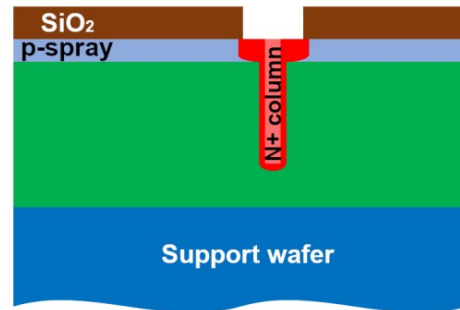
surface preparation



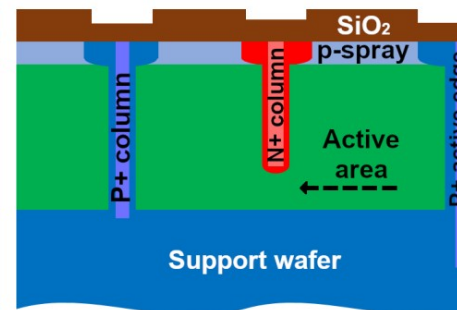
Lithography, DRIE etching



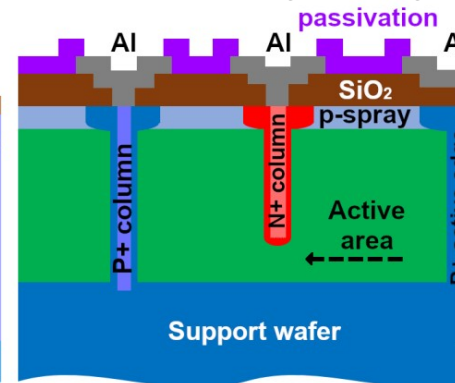
Polysilicon filling & doping



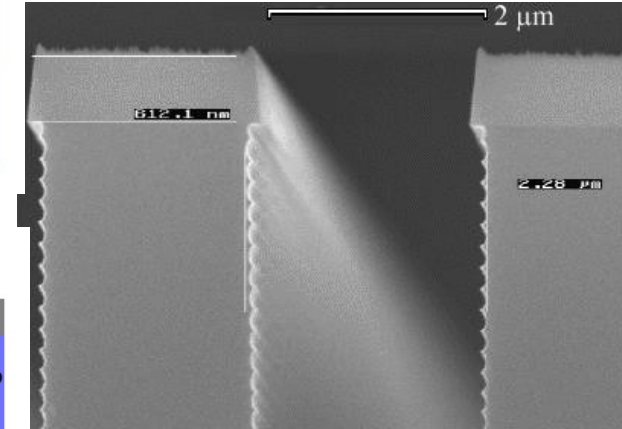
Lithography, n+ (surface) doping



Repeat for p columns...



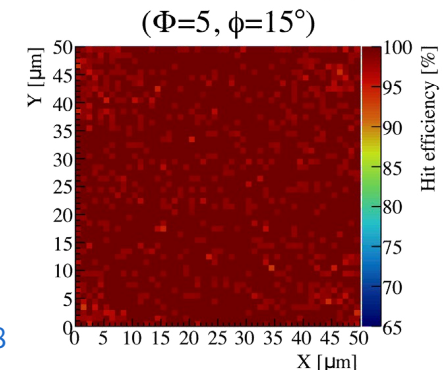
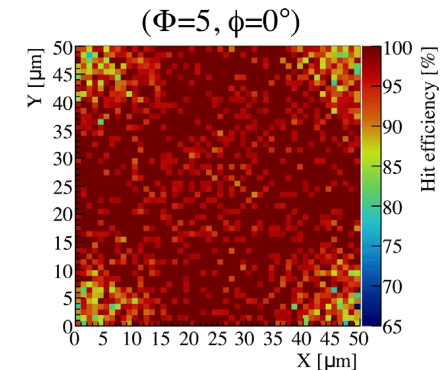
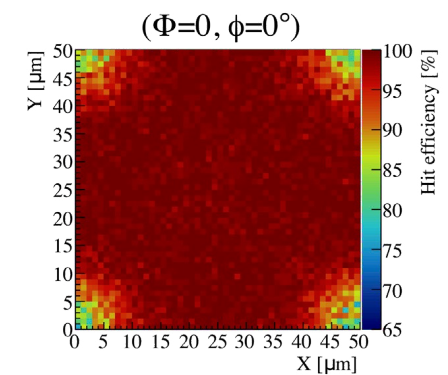
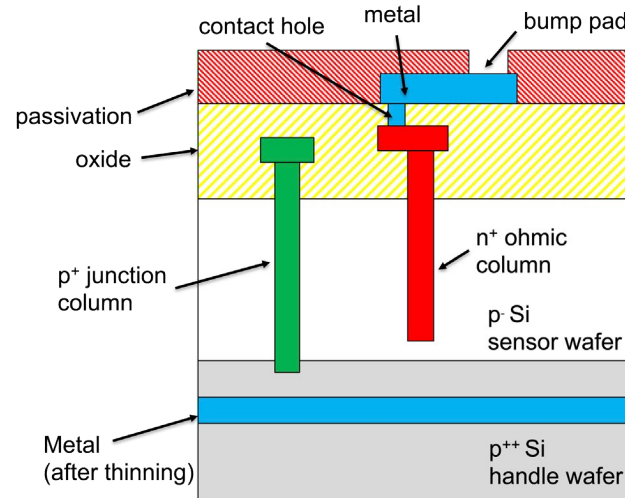
Standard surface processing



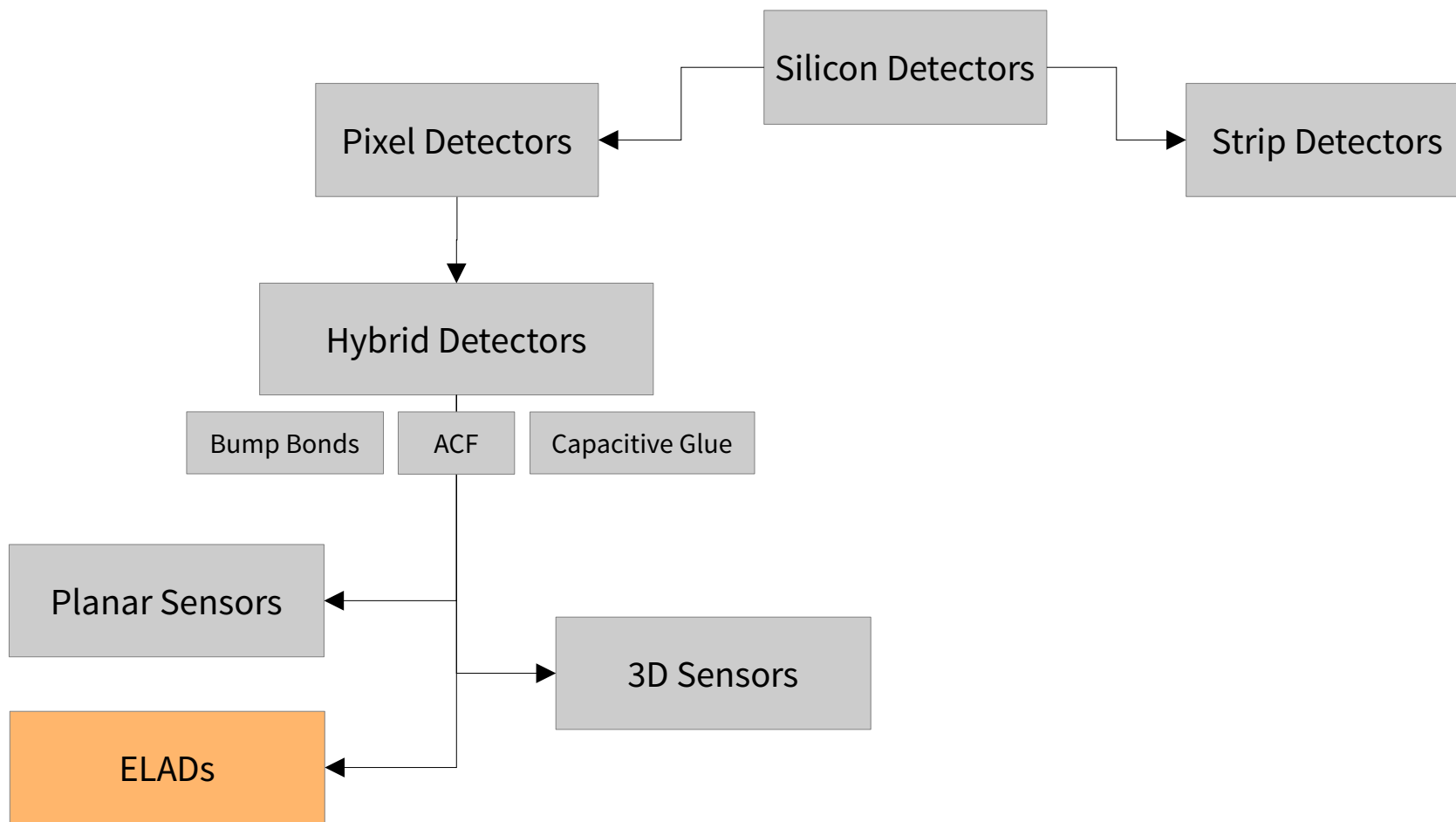
https://iopscience.iop.org/article/10.1088/1748-0221/17/08/P08003

Example: ATLAS ITk 3D Pixel Sensors

- Sensor for new inner tracker of ATLAS experiment
- 3D sensors for innermost layer of pixel detector
 - Very radiation hard (short drift times)
 - Different sensor layouts:
 - 50 x 50 μm
 - 25 x 100 μm
- At vertical incidence:
inefficiencies at backside columns
- Recovered even at slight inclination

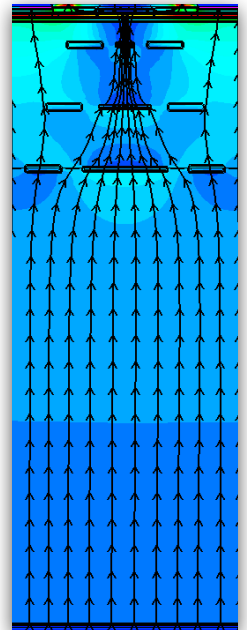
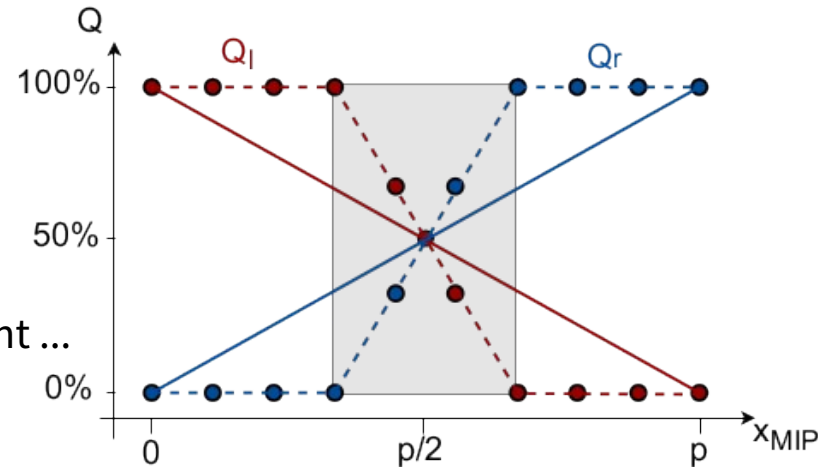
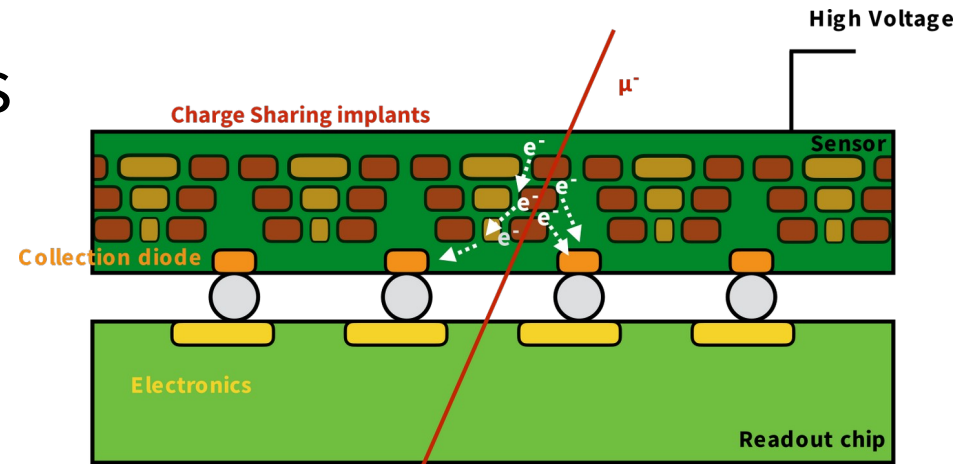


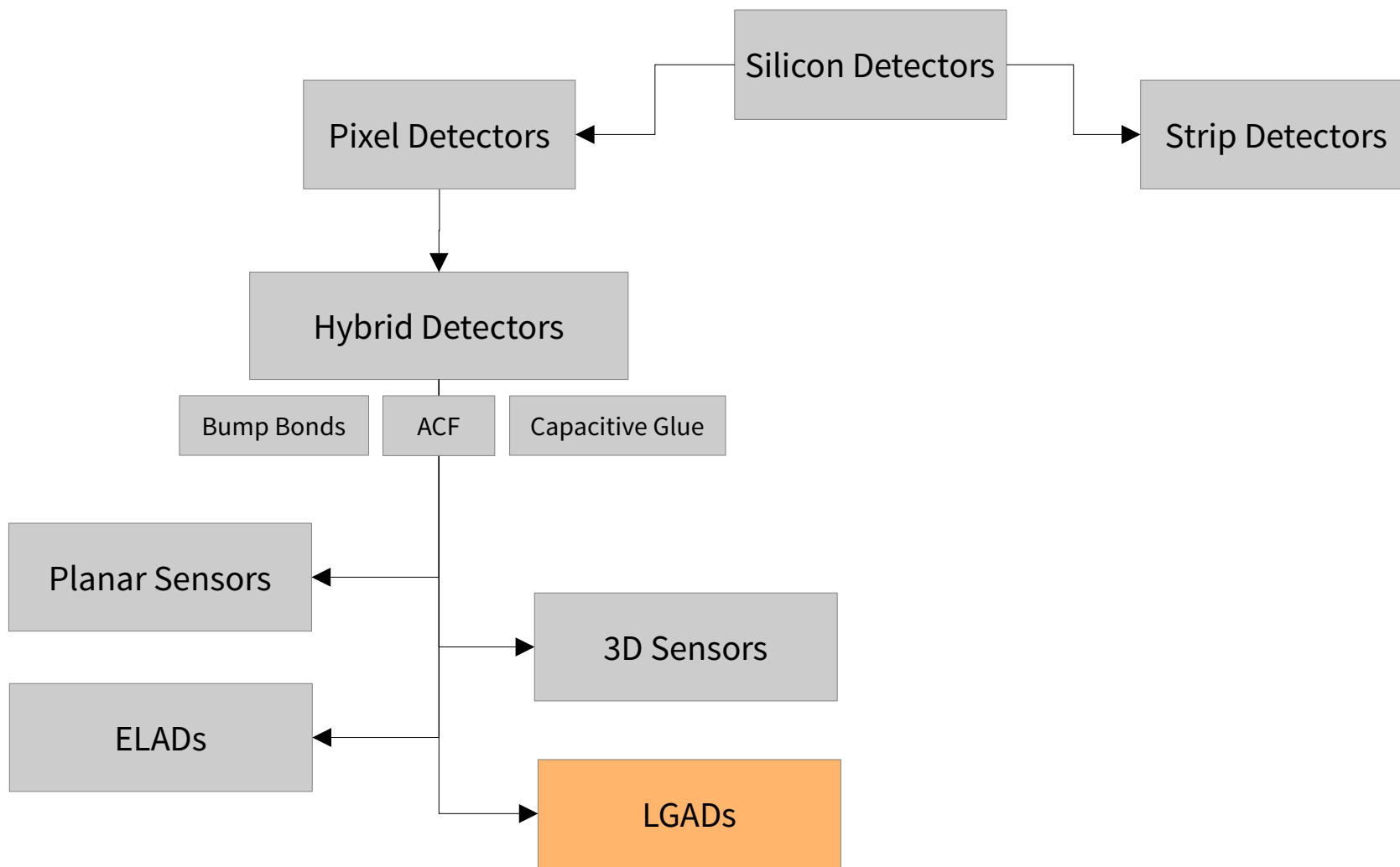
<https://doi.org/10.3389/fphy.2021.624668>



Enhanced Lateral Drift Detectors

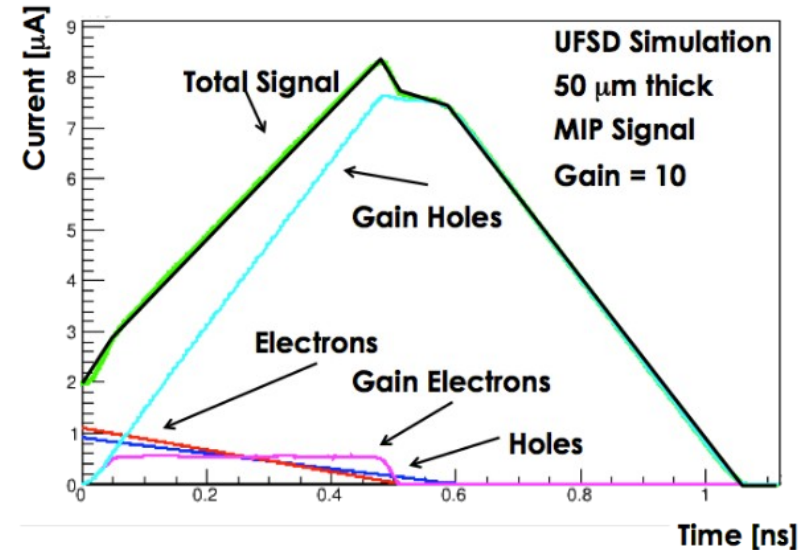
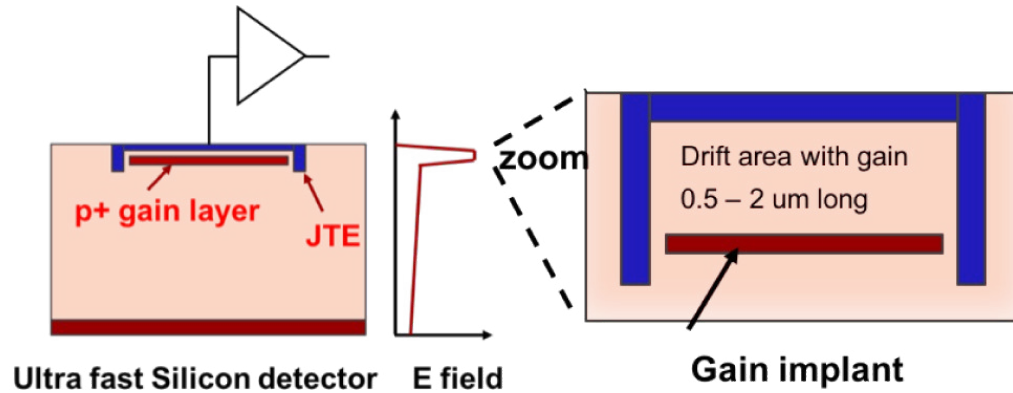
- Position resolution in **thin sensors** limited to $d / \sqrt{12}$ (almost no charge sharing)
- Concept: **enhance charge sharing** in Enhanced Lateral Drift sensors (ELAD)
 - Close to theoretical optimum: linear charge sharing
 - Deep implants to alter field, improve resolution
 - Lateral spread of charges during drift
- Challenges:
 - Complex production process: epi-growth / implant / epi-growth / implant ...
 - Low-field regions (recombination)





Low Gain Avalanche Diodes (LGADs)

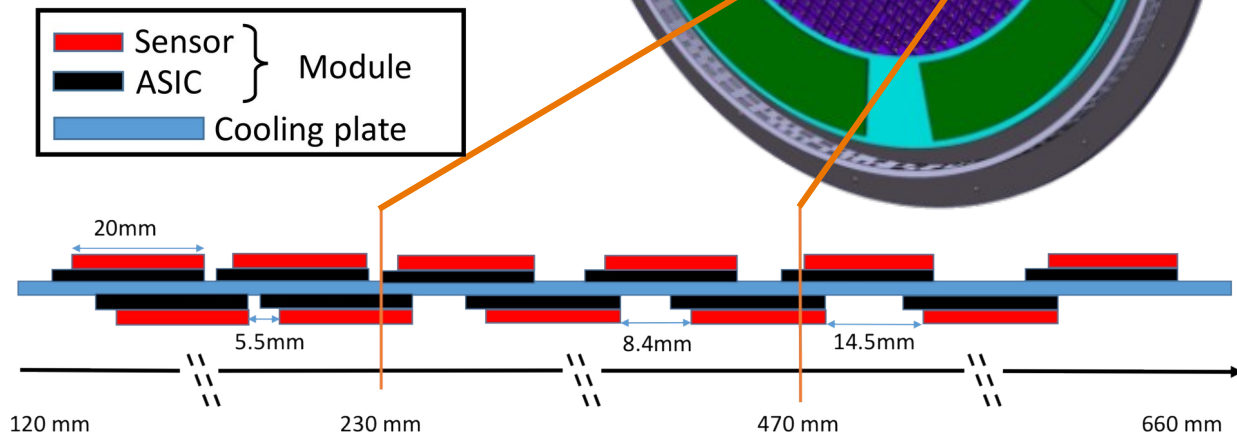
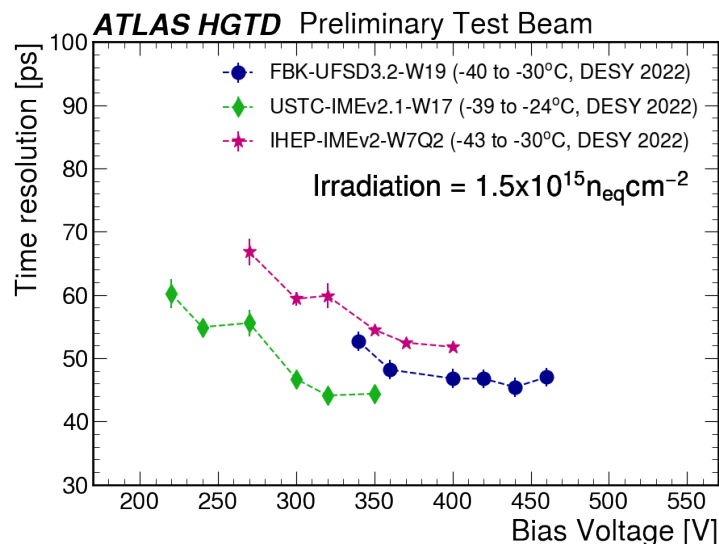
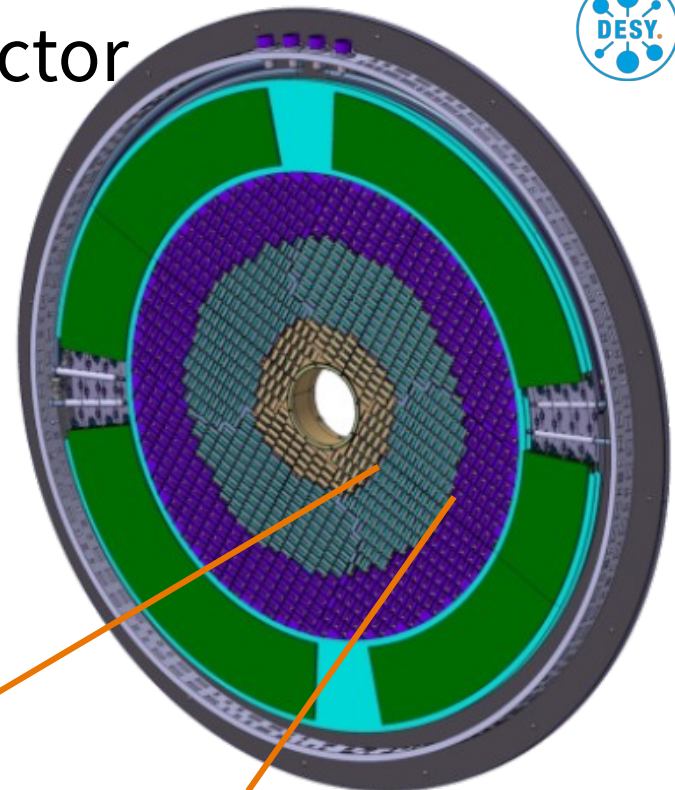
- High electric fields: secondary ionization by charge carriers becomes possible → **Impact Ionization**
 - Similar to charge multiplication in gaseous detectors
- High electric fields in small sensor volume fraction generated via thin doping layer



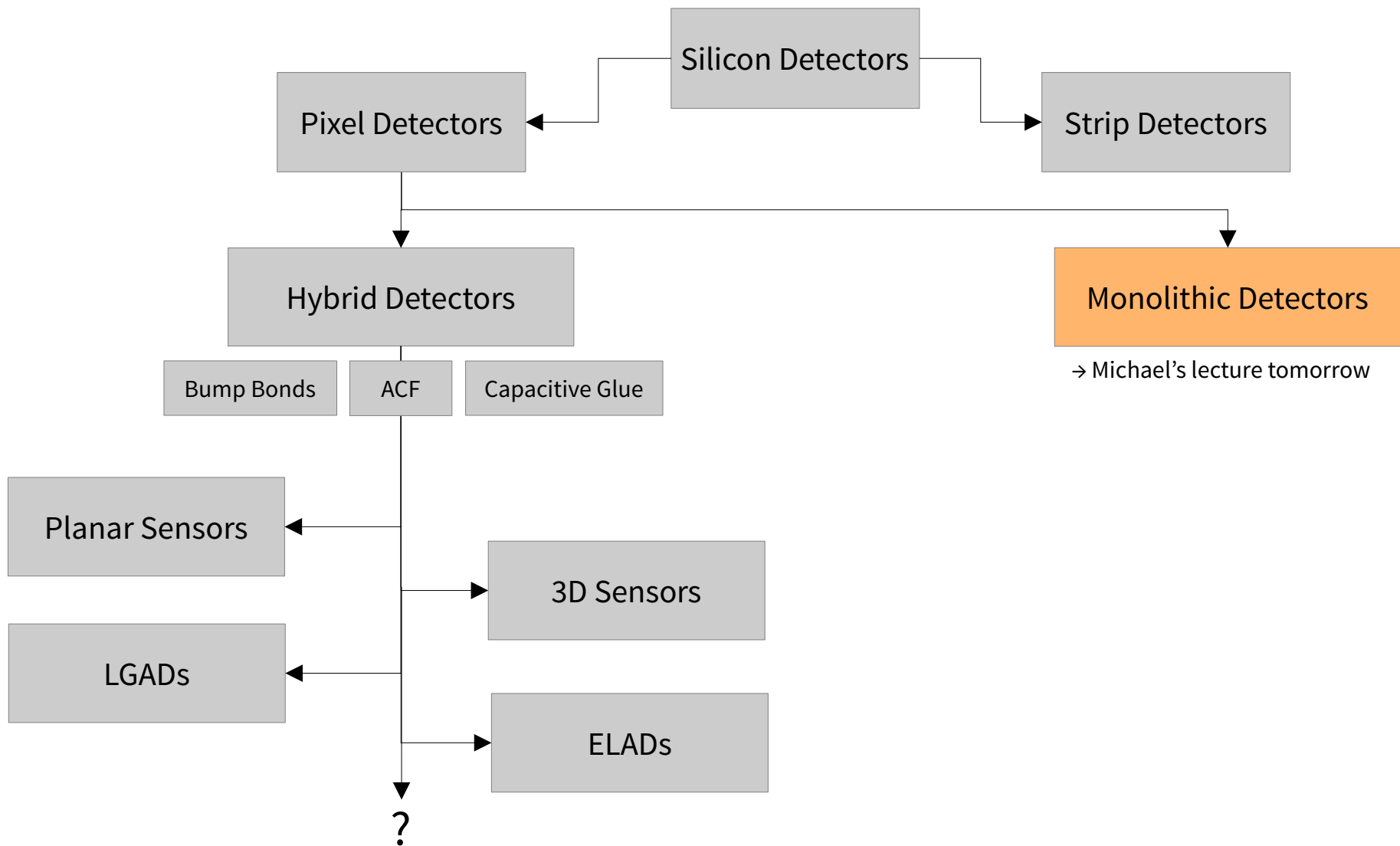
- Different types of LGADs: pads, iLGADs, TI-LGADs, ...
- “Typical” silicon detectors: $\sigma > 1 \text{ ns}$
- LGADs (Low Gain Avalanche Diodes) / UFSDs: $\sigma > 30 \text{ ps}$

The ATLAS High Granularity Timing Detector

- Mitigate tracking issues from high pile-up at HL-LHC
 - Required timing resolution better than 50 ps/track
 - $\sim 3.7 \times 10^6$ channels with 6.4 m² area
 - Radiation hardness 2.5×10^{15} N_{eq}/cm² and 2.0 MGy
- LGADs with dedicated readout ASIC (ALTIROC)

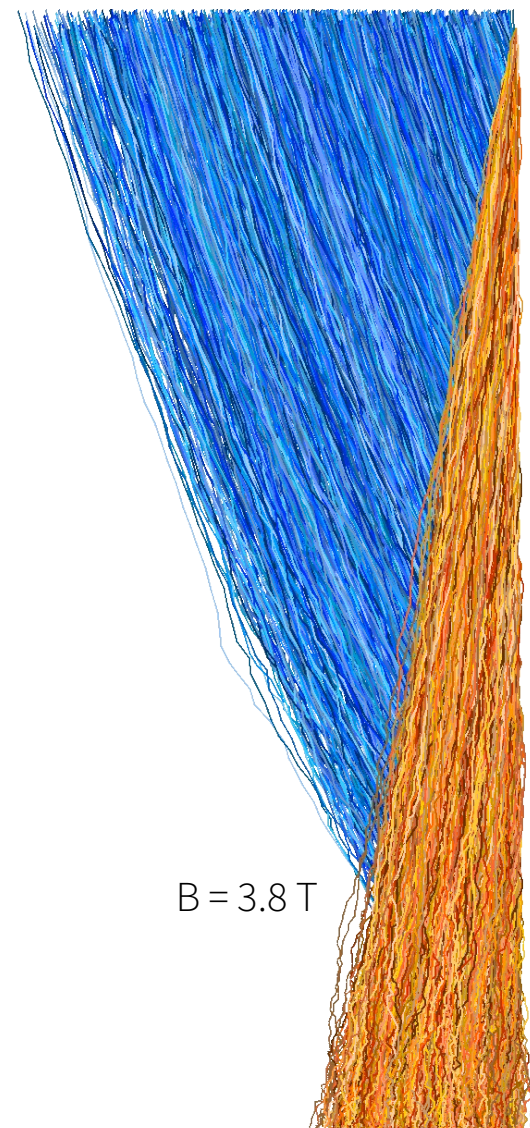


<https://doi.org/10.1016/j.nima.2022.166628>

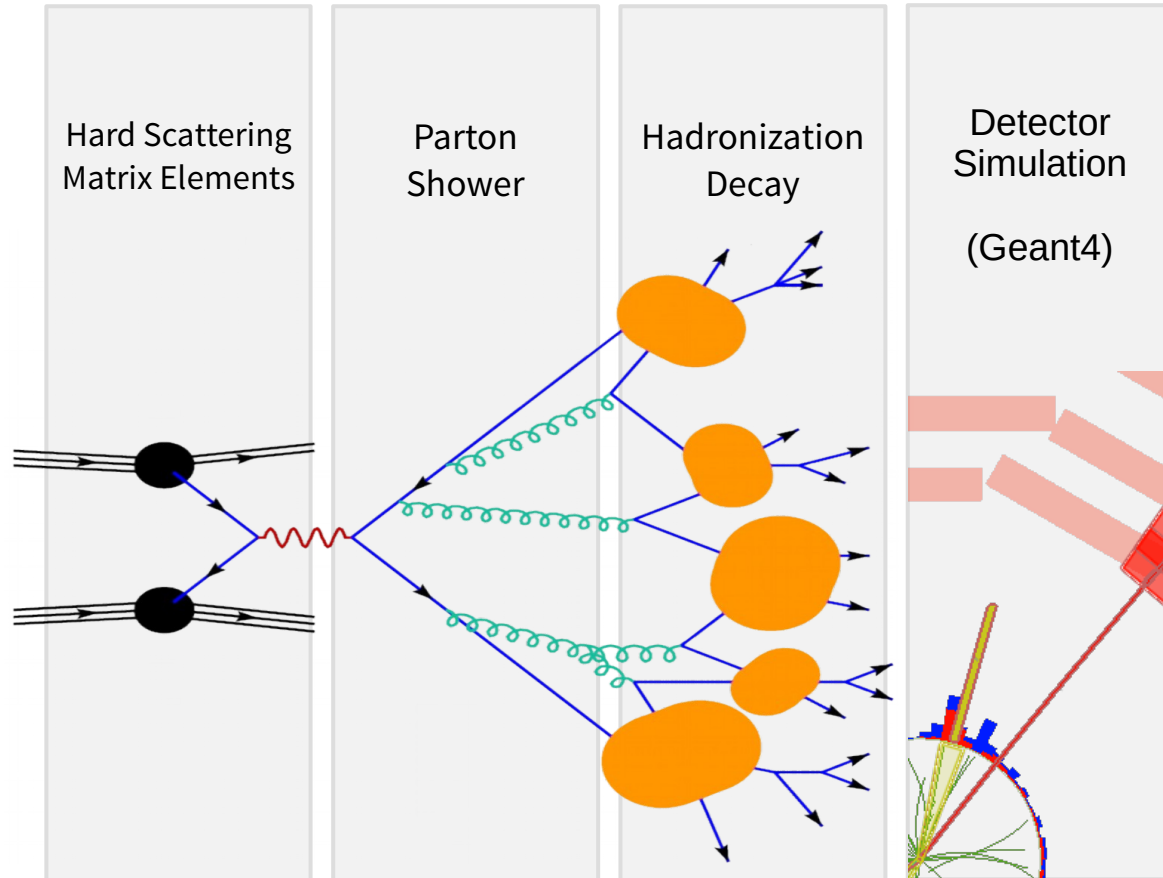


Understanding Your Detector

...by Means of Monte Carlo Simulations



Monte Carlo from Start to End



Geant4 – GEometry ANd Tracking

→ Lab Exercise 10



- Toolkit to simulate interaction of particles with matter
- Open Source project, written in C++ using Object Orientation
- Typically new feature versions are released once a year

- It is a **toolkit** → a collection of tools for simulations

- Coding is *always* required for simulations
- There is not such concept as “Geant4 defaults”

- Learning-by-reading: examples in source code

- **Basic examples:** overview of the Geant4 tools
- **Extended examples:** showing specific Geant4 functionalities
- **Advanced Examples:** Geant4 tools in real-life applications

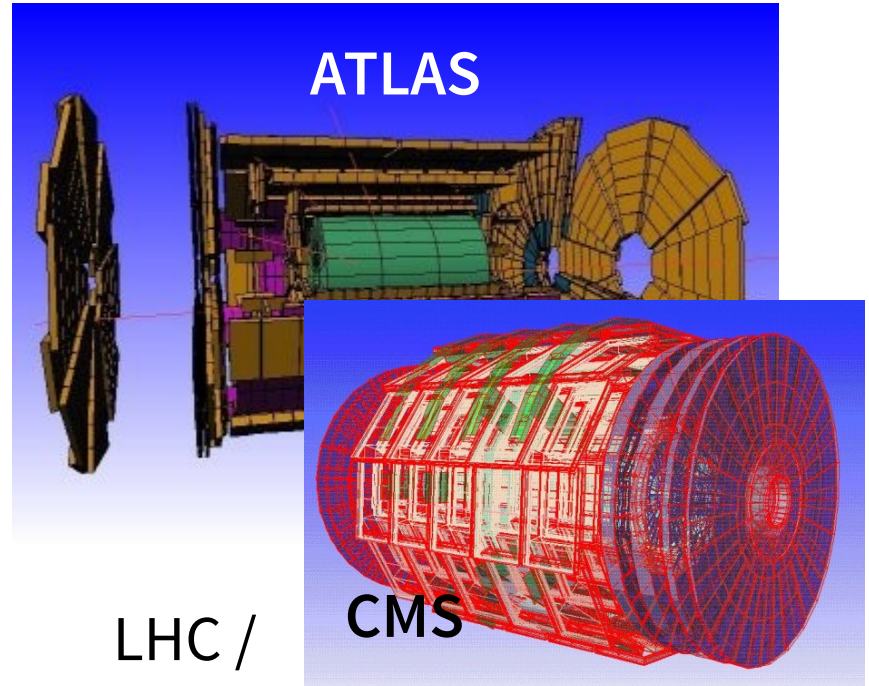
```
int main(int argc, char** argv) {
    G4RunManager* runManager = new G4RunManager;
    runManager->SetUserInitialization(new MyDetectorConstruction());

    // Physics list
    G4VModularPhysicsList* physicsList = new MyPhysicsList;
    physicsList->SetVerboseLevel(1);
    runManager->SetUserInitialization(physicsList);

    // User actions initialization
    runManager->SetUserInitialization(new MyActionInitialization());

    ...
}
```

Applications wherever particles are involved...

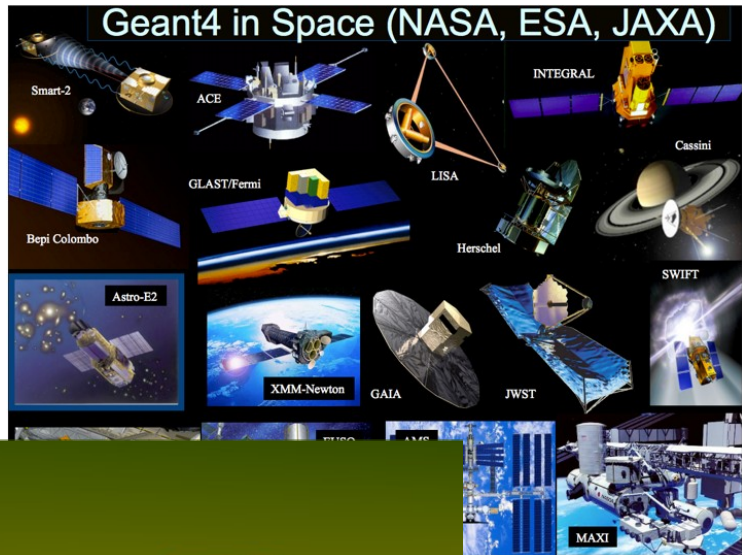


ATLAS

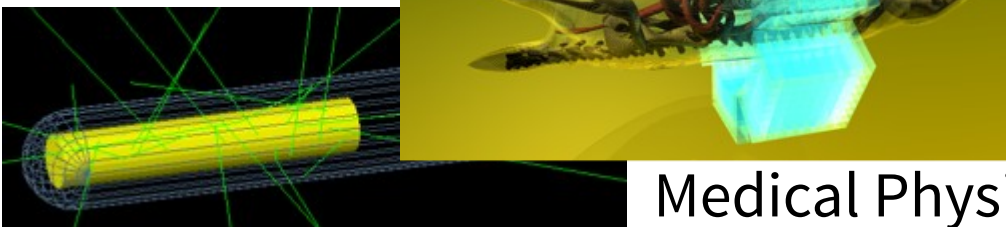
CMS

LHC /
particle physics

Satellites /
Space



Medical Physics



Core Concepts of Geant4

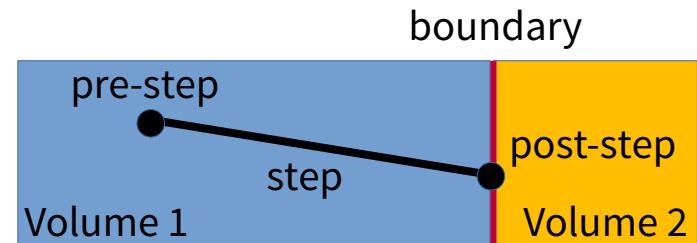
The Basic concepts at the core of Geant4 are:

- **The run** represents a set of events which share a common setup: geometry, beam type and configuration of physics processes.
- **The event** represents all information (tracks, interaction) that result from one or more initial particles
- **A process** is usually a physics process - something which results from the interaction of a particle with an atom of the material it is crossing.
- **The track** represents the snapshot of the current state of simulating one particle track, and stores information on the particle creation
- **The step** represents how the current particle is being moved

Tracking in Geant4

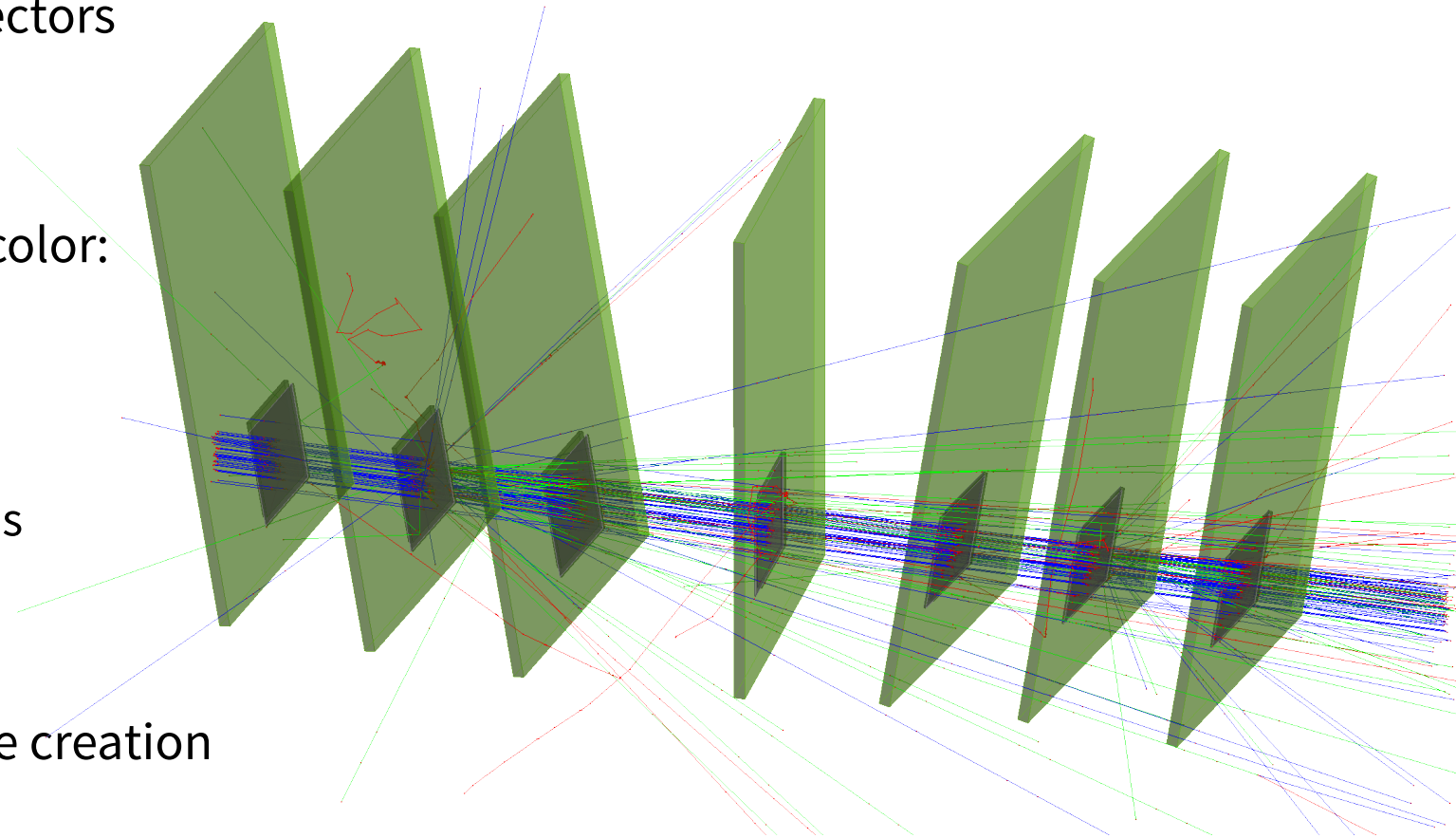
Following particles is done by stepping:

- Initializing of the track
- Polling of all processes (interactions) to see how far each one will occur next (free path)
- Determination of the minimum length, which is the length of the next step.
This identifies also the winning process, the one which occurs at the end point of the step
- Calculating amount of energy lost along the length of the step
- Calling of the winning process to obtain results of the interaction including change in energy, momentum direction, new particles created, ...
- Determination of volume the track enters next at the end of a step (if on boundary)

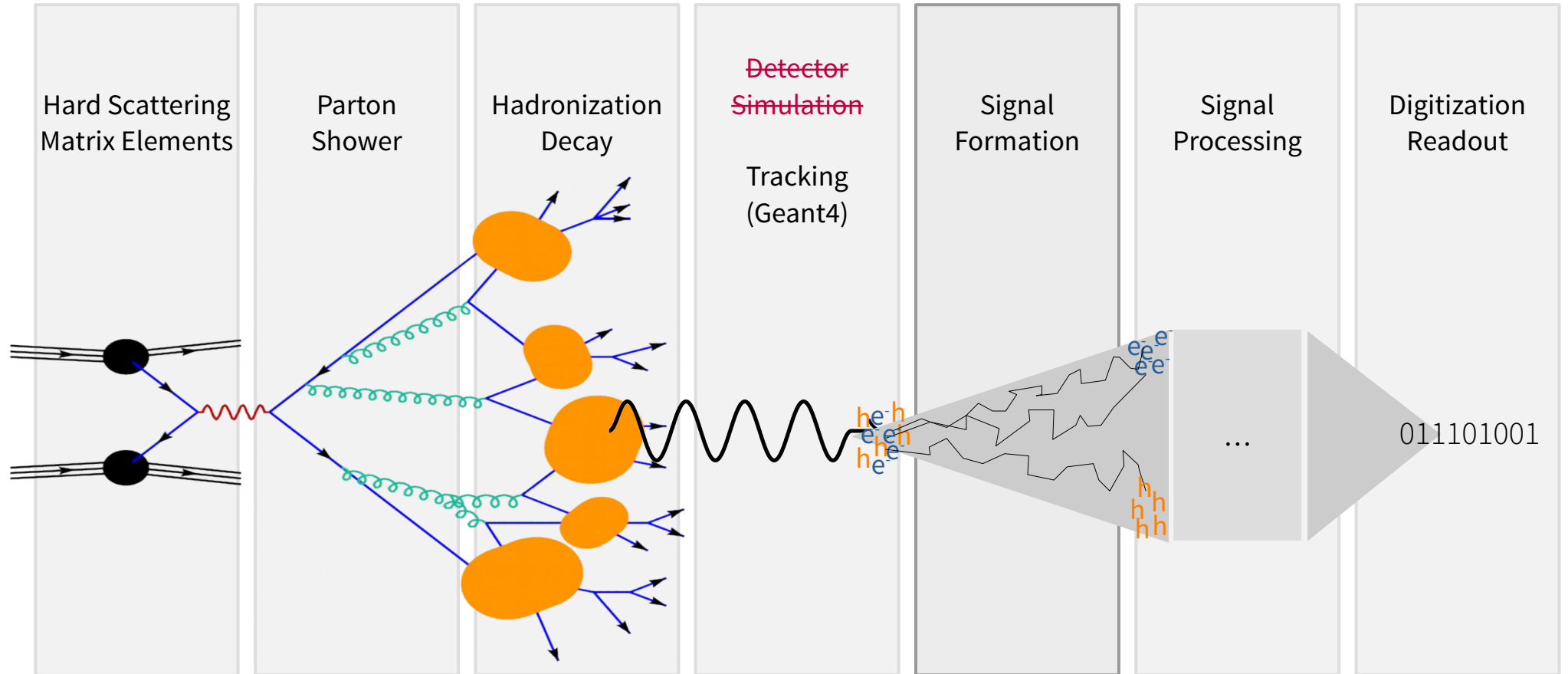
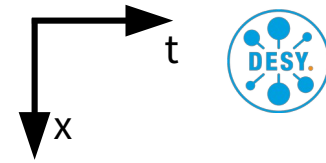


Example: Visualization of Geant4 Tracking

- Seven silicon detectors in a Pion beam
- Particle types by color:
 - Blue: Pions
 - Red: Electrons
 - Green: Gammas
- Scattering, secondary particle creation



Monte Carlo from Start to End

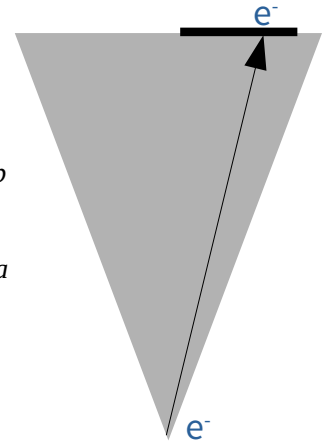


O(1) – Projecting Charge Carriers

- With linear electric field, calculate approximate total drift time via analytical approximation of mobility integral
- For each (group of) charge carrier,
 - Calculate total drift time
 - Calculate total diffusion offset for this time
 - Put charge carrier on sensor surface, with offset drawn from Gaussian distribution of width σ_x
- Very fast simulation, few calculations
- Only works for linear electric field approximations (reasonable for many thick planar sensors) and without magnetic field

$$t = \int \frac{1}{v} ds \approx \frac{1}{\mu_0} \left[\frac{\ln(E(s))}{k} + \frac{s}{E_c} \right]_a^b$$

$$E(s) = ks + E_0$$

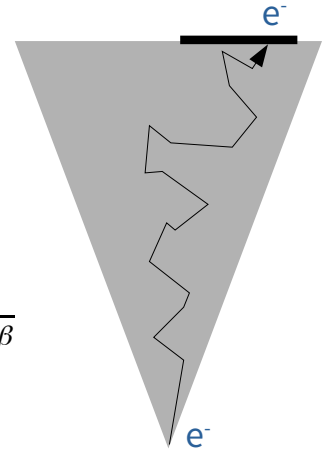


O(N) – Integration of Equations of Motion

- Successive integration of charge carrier motion
- Take each (group of) charge carrier
 - Calculate mobility μ from local electric (and magnetic) field (e.g. using Jacoboni/Canali parametrization)
 - Calculate velocity
 - Make step, add diffusion offset from Gaussian distribution
 - Repeat N times until sensor surface is reached
- Using 4th order Runge-Kutta-Fehlberg method
 - Adaptive step size according to position uncertainty (embedded 5th order)
 - Method allows description of drift in complex field configurations

$$\mu = \frac{v_m}{E_c} \frac{1}{(1 + (E/E_c)^\beta)^{1/\beta}}$$

$$\sigma_x = \sqrt{\frac{2k_b T}{e} \mu t}$$



$O(2 \times N \times M)$ – Induced Signal at Electrodes

- Successive integration of motion, calculating induced charge per step
- Take each (group of) charge carrier
 - Calculate mobility & velocity from local fields
 - Make step, add diffusion offset from Gaussian distribution
 - Get induced charge from weighting potential difference for M neighbors
 - Repeat N times until sensor surface is reached
- Allows time-resolved simulation

$$Q_n^{ind.} = \int_{t_{n-1}}^{t_n} I_n^{ind.} dt = q[\phi(X_n) - \phi(x_{n-1})]$$
 - Requires weighting potential, might not be trivial to obtain
- Time consuming:
 - Calculation for all neighboring electrodes for every step
 - Requires propagating both electrons and holes (x2)

